

Principles of Micro- and Nanofabrication for Electronic and Photonic Devices

Packaging and Integration

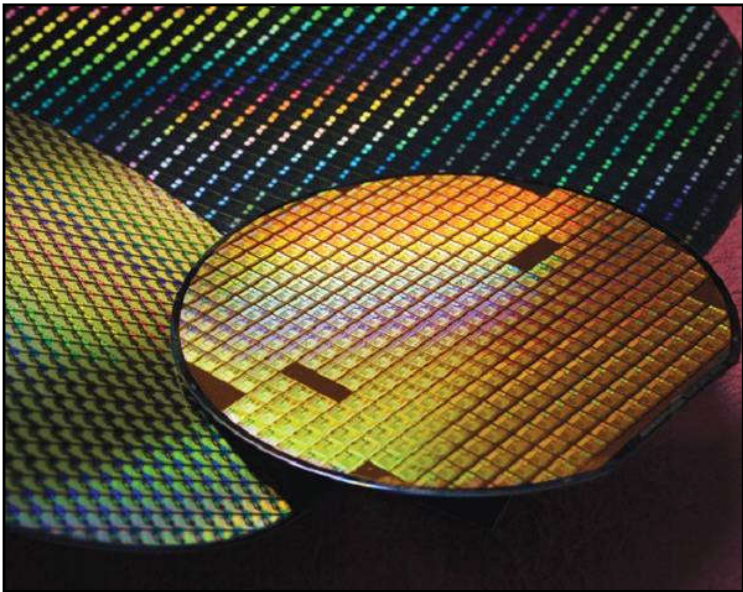
Xing Sheng 盛兴



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Tsinghua University**

xingsheng@tsinghua.edu.cn

Packaging



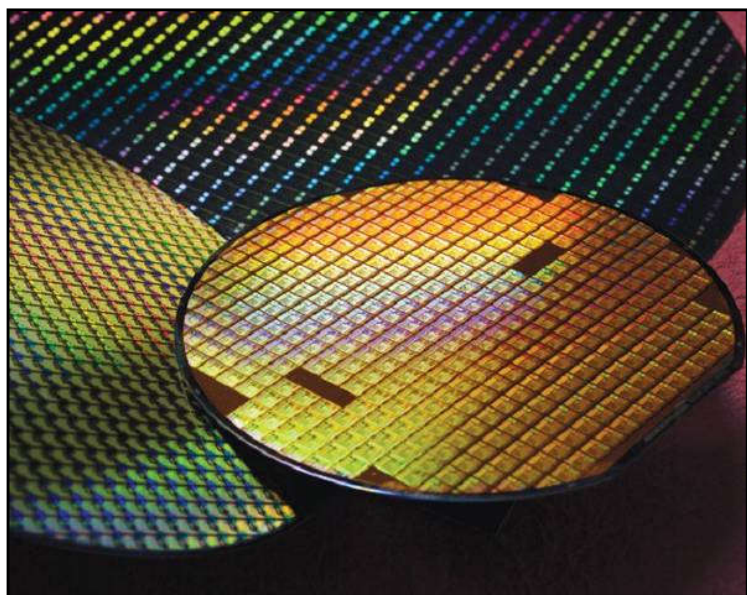
Si wafers



IC chips

[Video](#)

Packaging



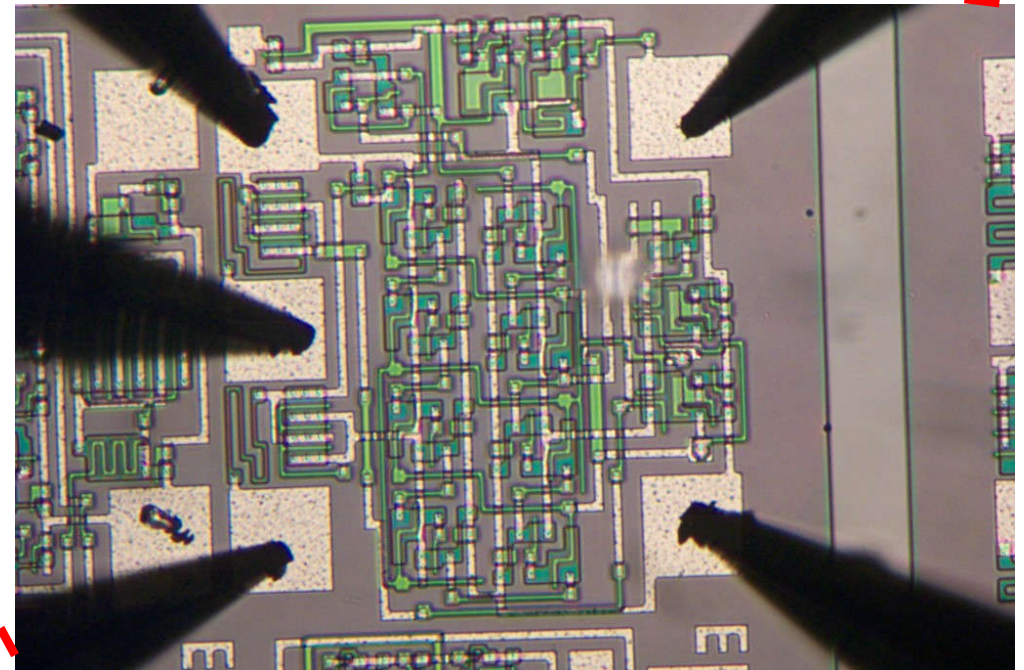
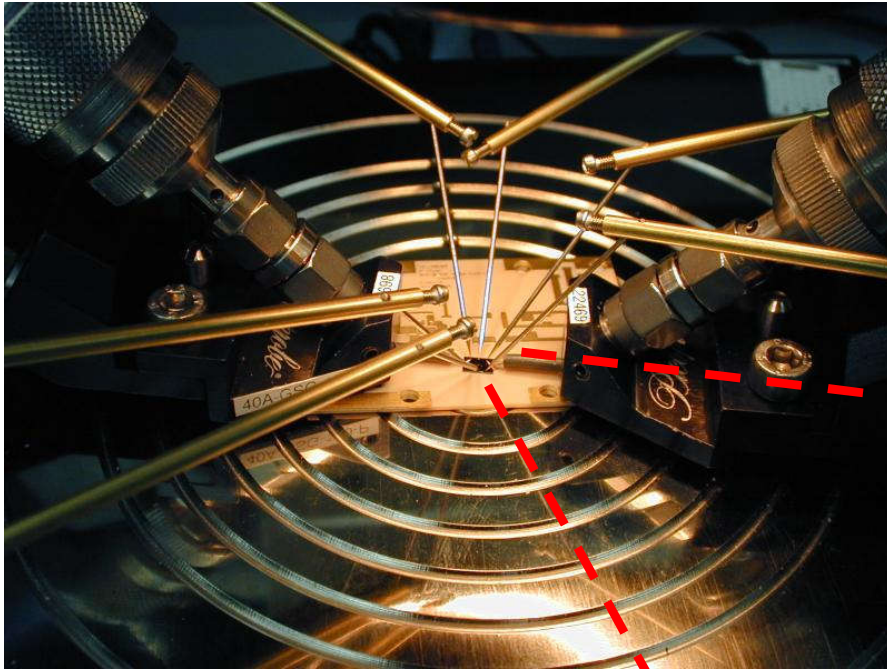
Si wafers



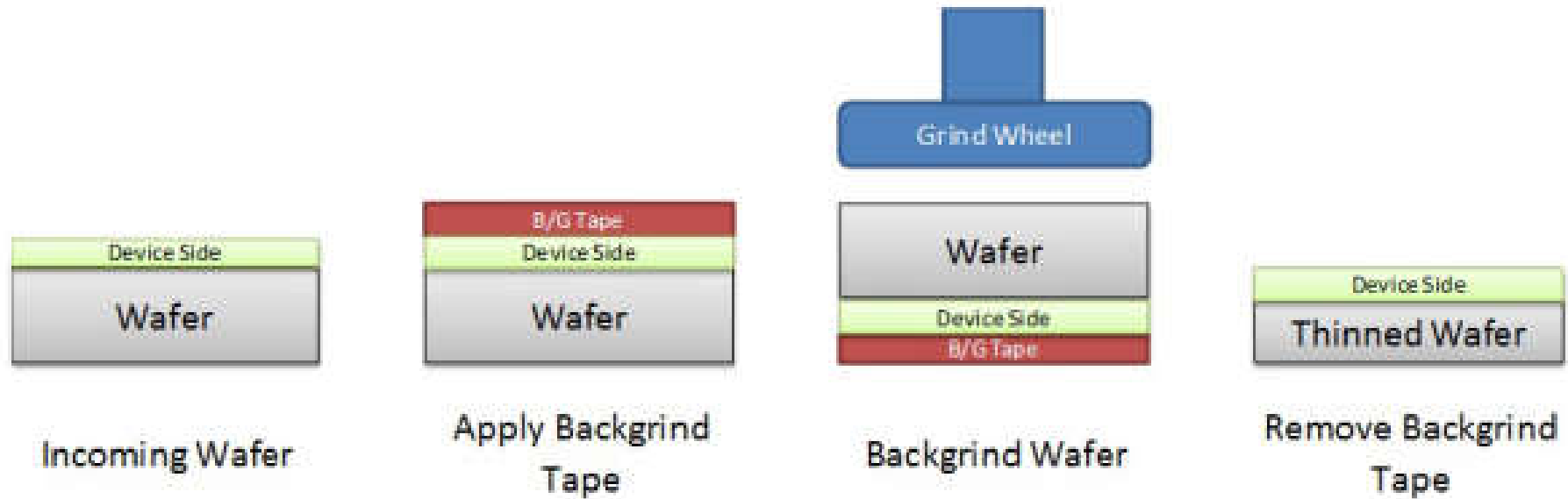
IC chips

test, wafer thinning, dicing, bonding, ...

Probe Test

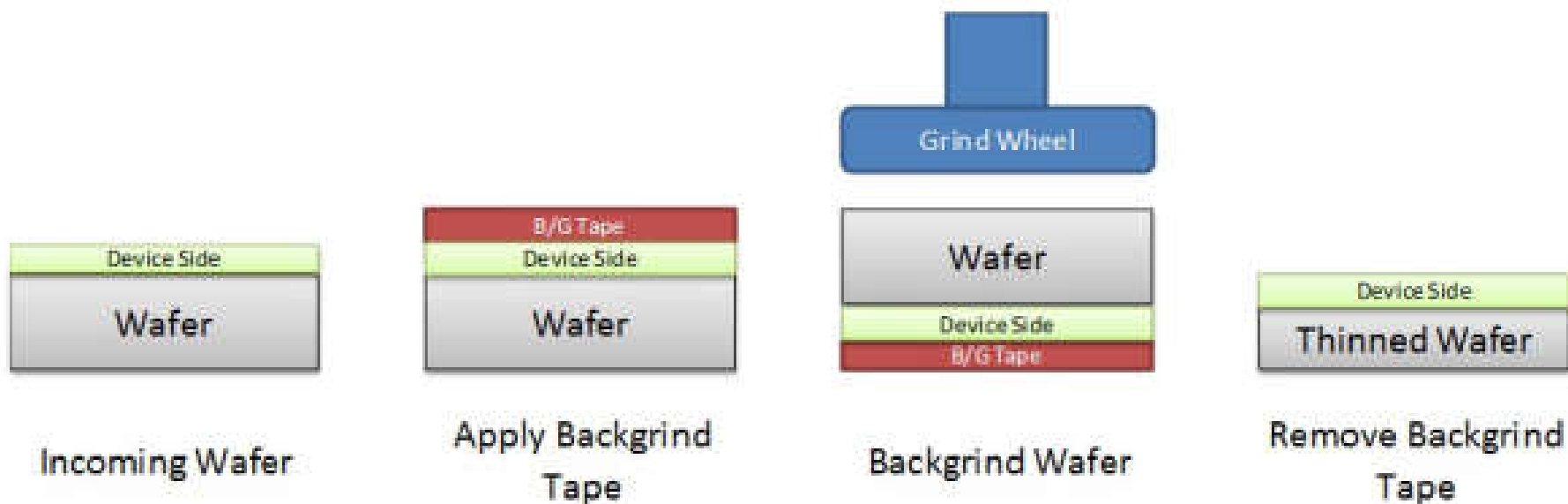


Wafer Thinning

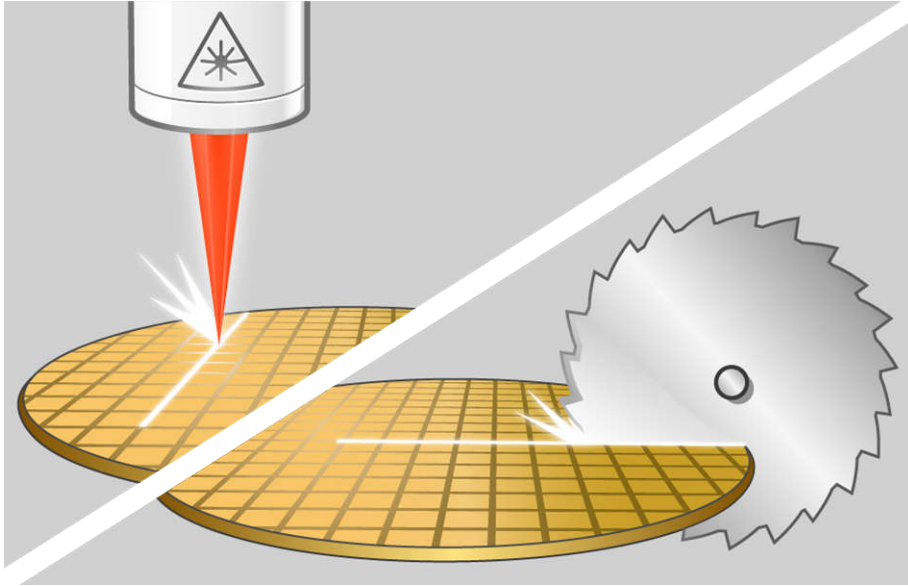


**typically, $\sim 100 \mu\text{m}$
can be as thin as $20 \mu\text{m}$**

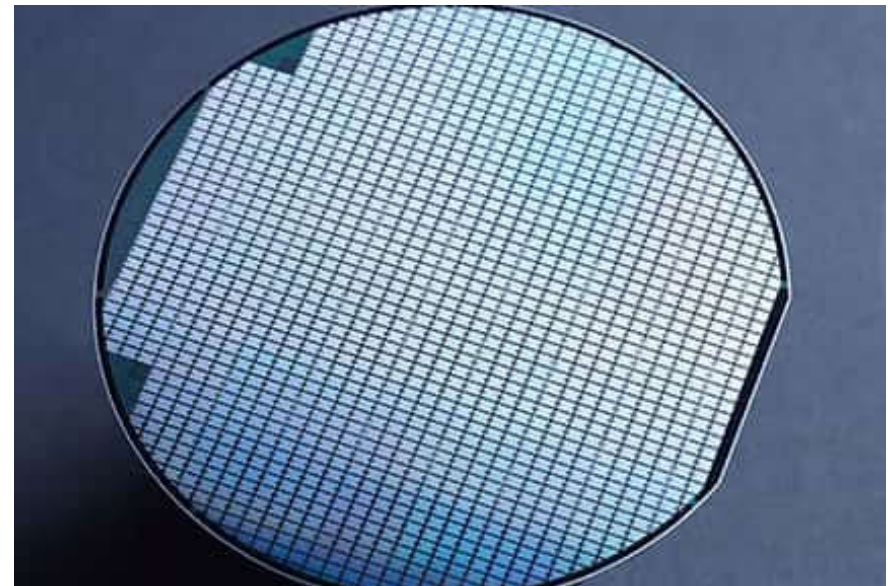
Wafer Thinning



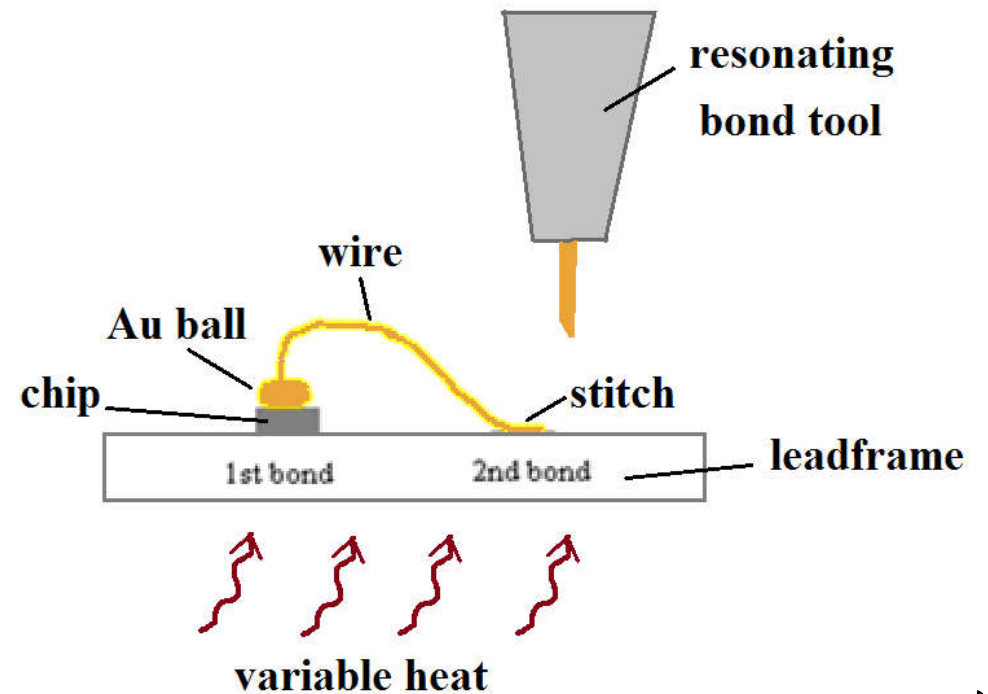
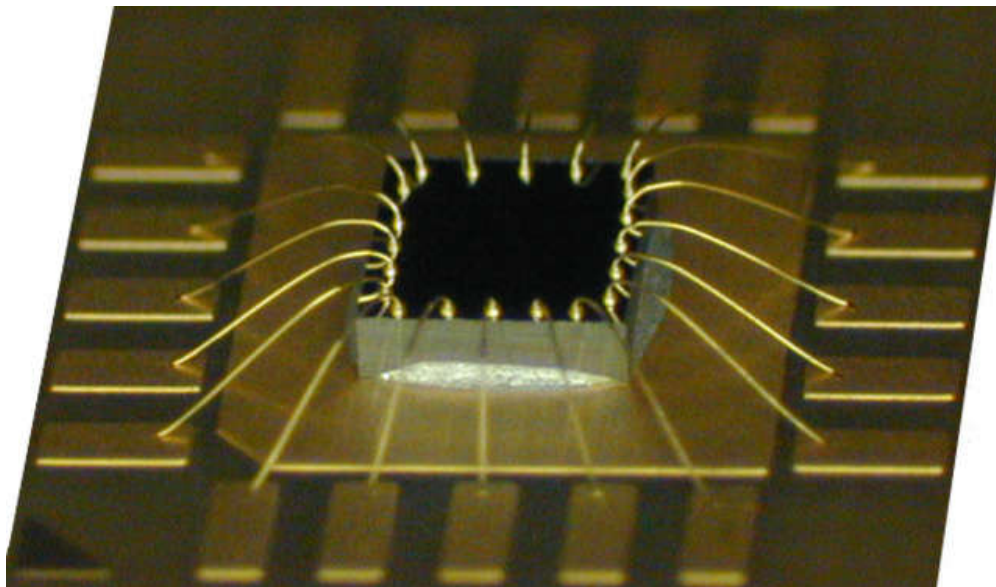
Dicing



laser
saw
plasma
...

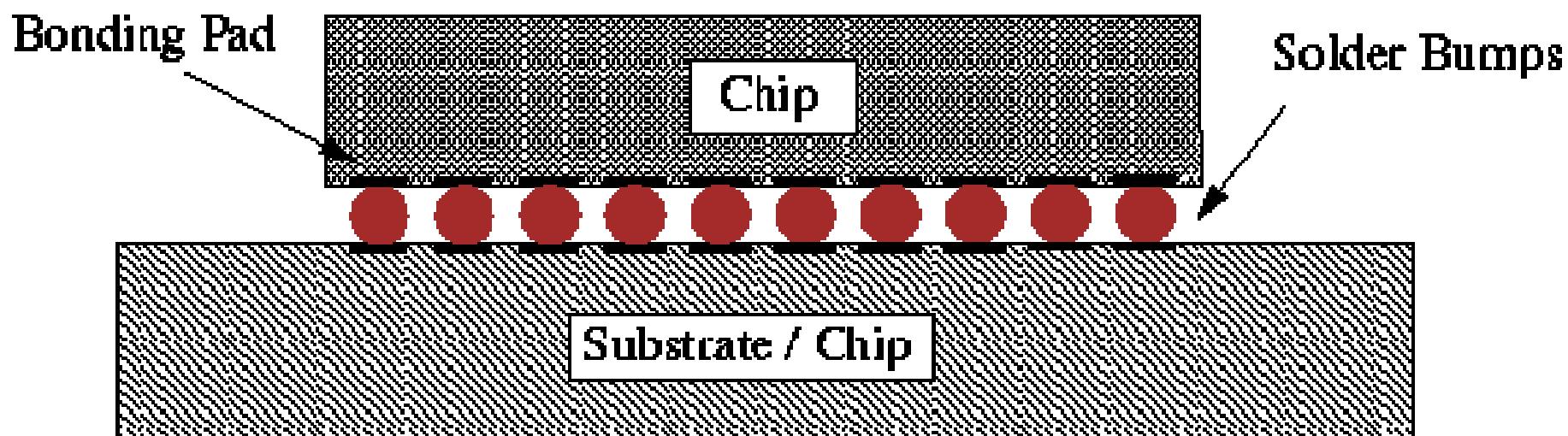
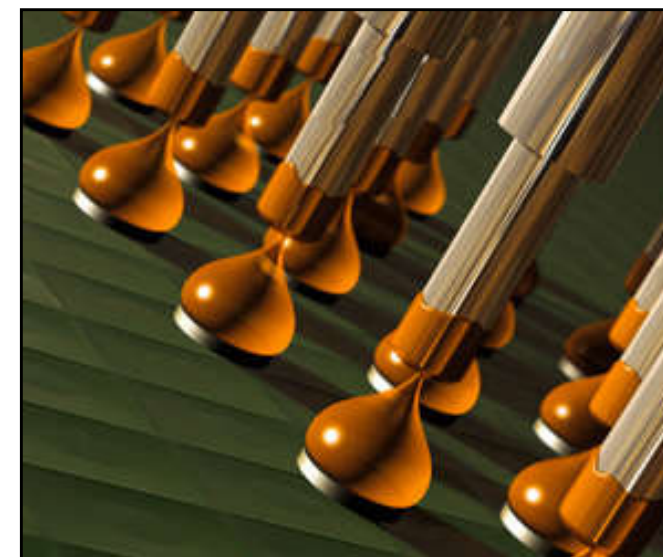
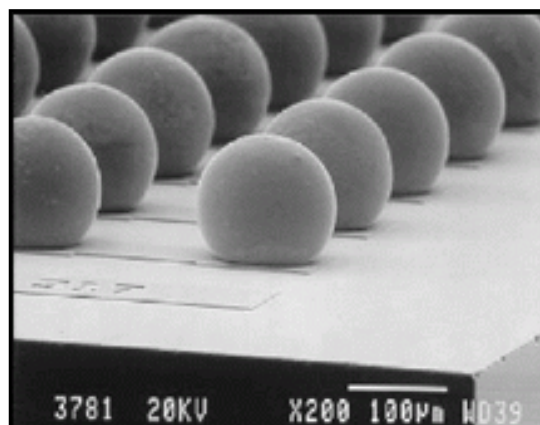


Wire Bonding

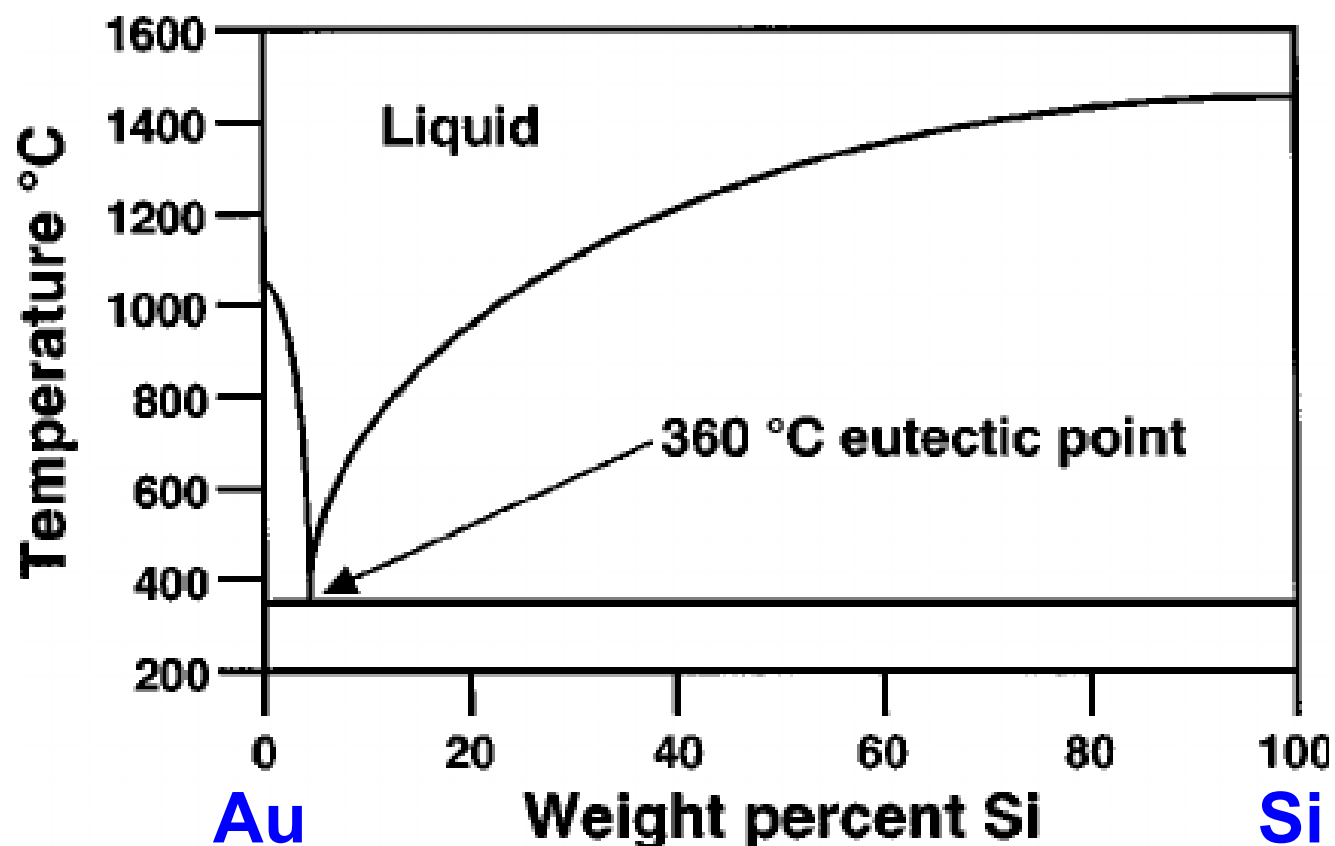
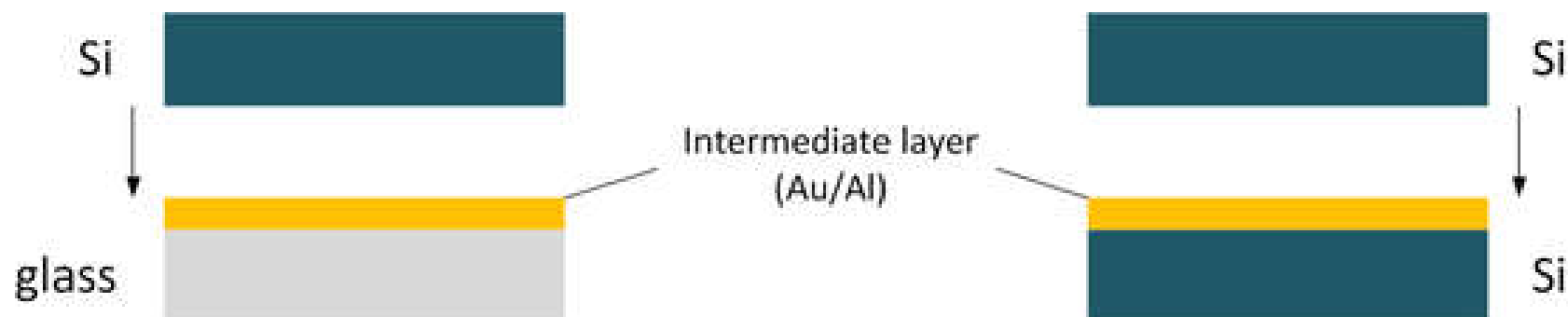


'Flip-Chip' Die Bonding

Metals alloys: Pb, Cu, Ag, Sn, ...
low melting point

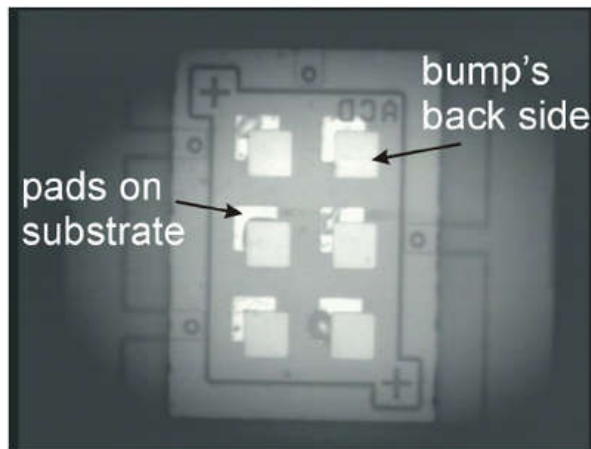


Eutectic Bonding

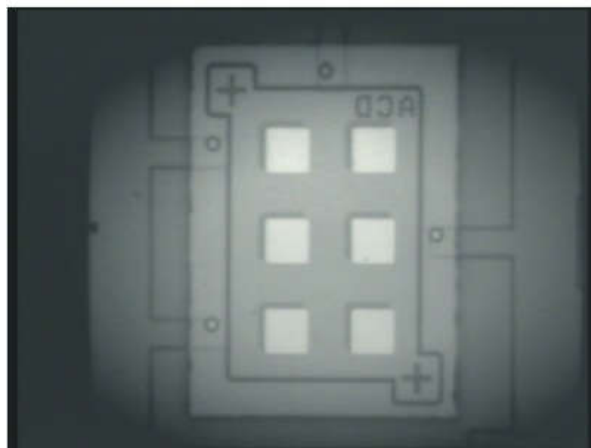
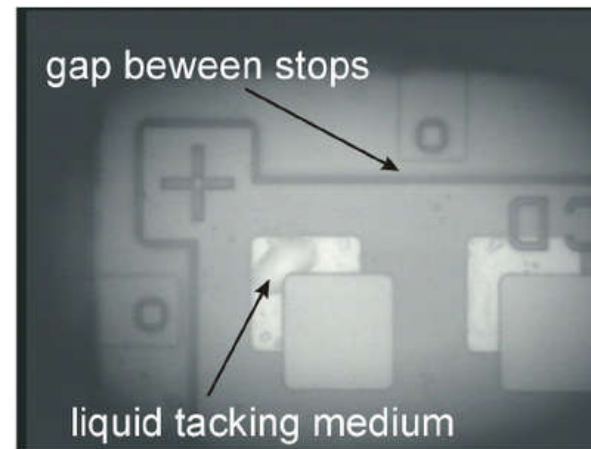


Infrared Imaging

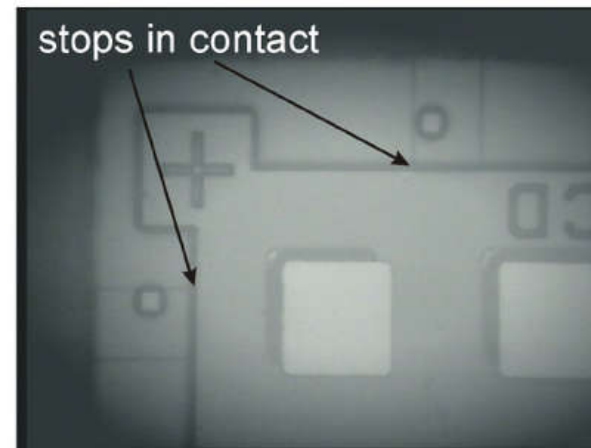
Si is transparent at near-infrared (> 1100 nm)



After pick & place: stops are not in contact to each other

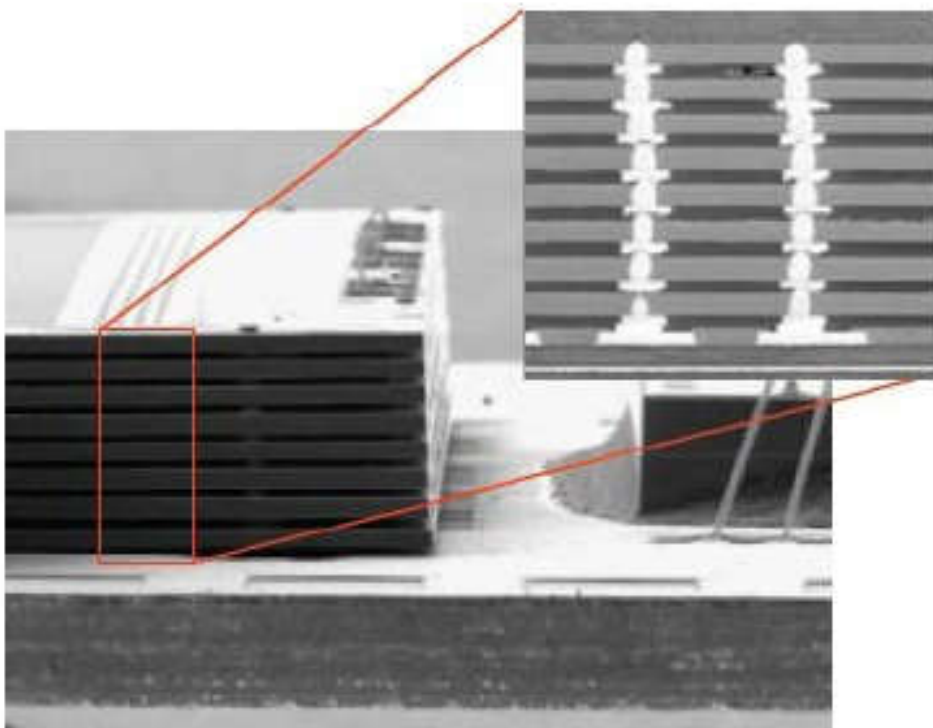


After reflow: stops have reached each other

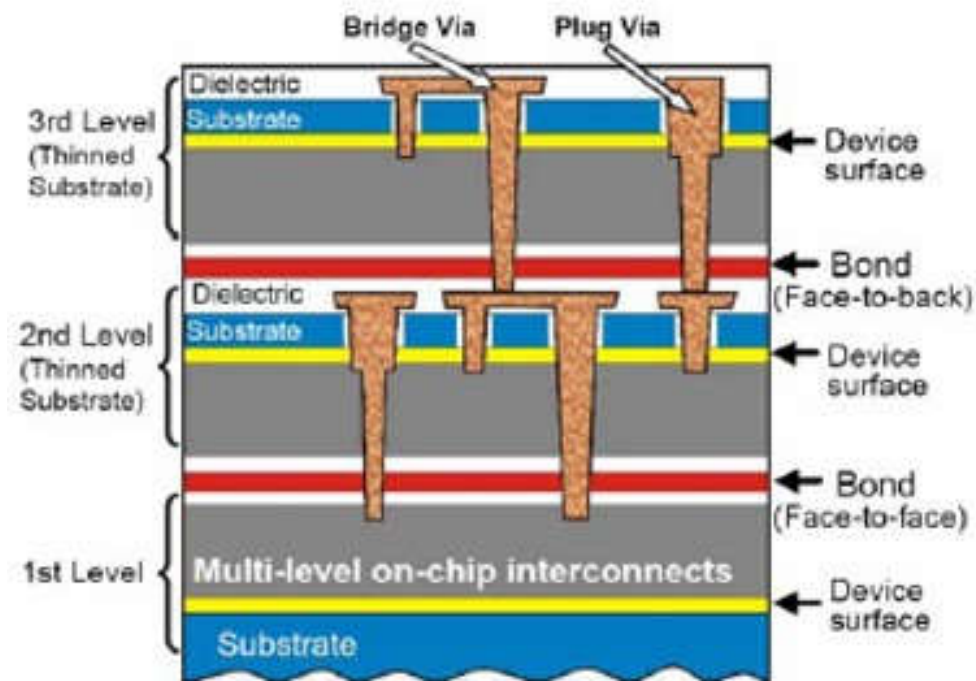


Through-Silicon Via (TSV)

Conductive channels through the silicon wafer



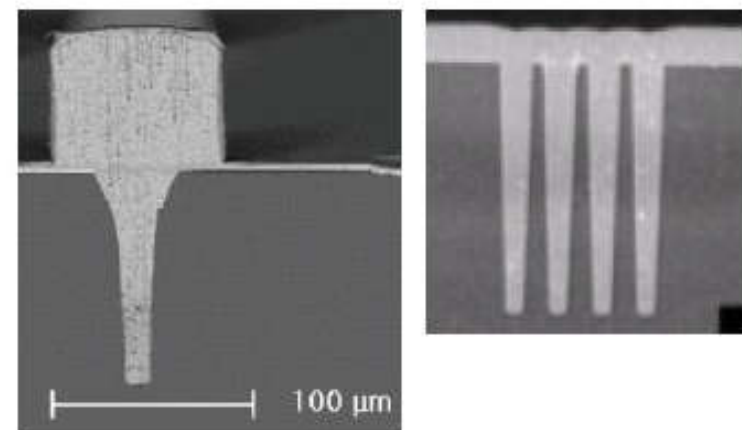
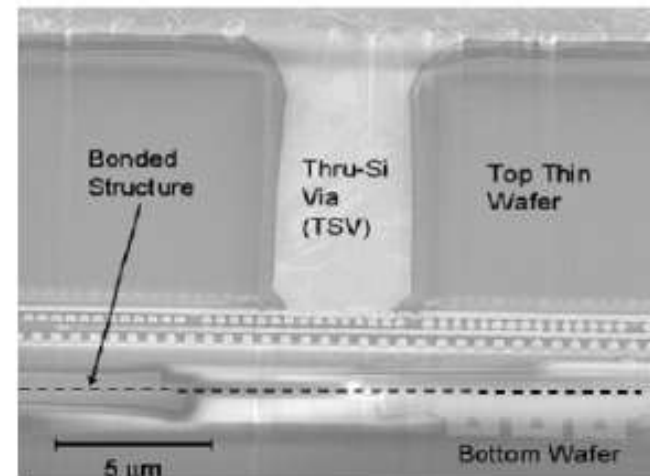
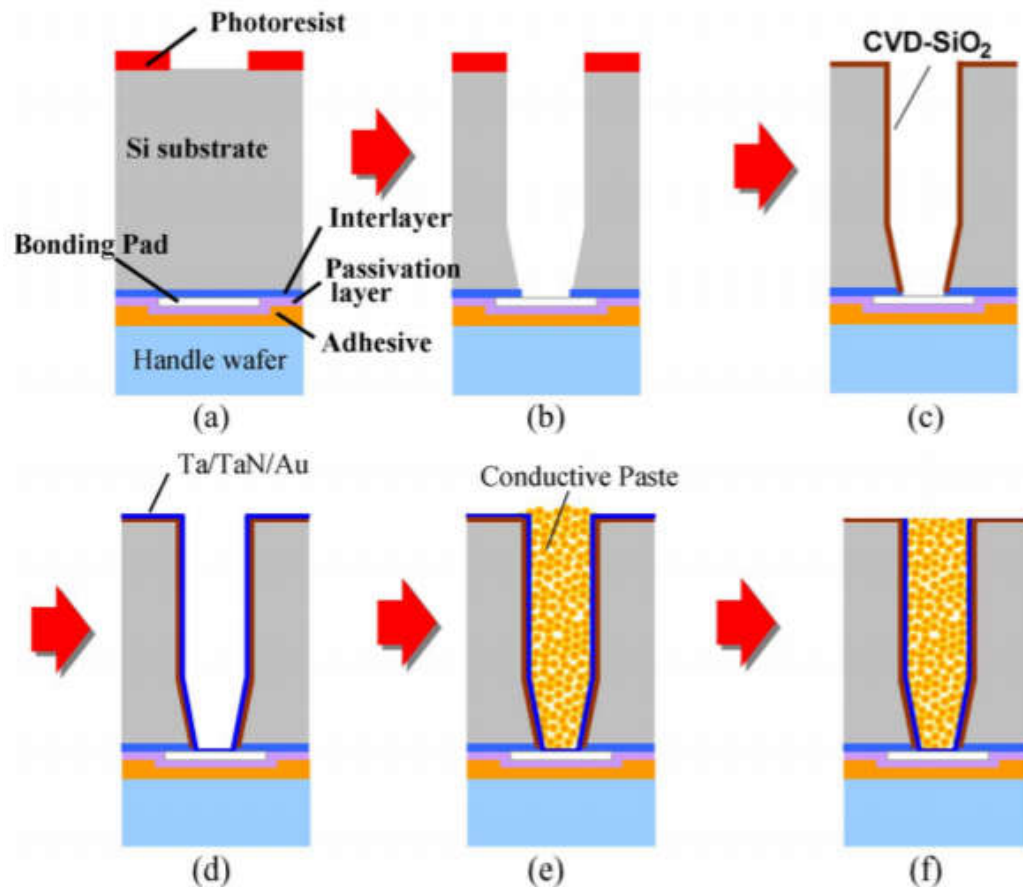
Source : Samsung Electronics



James Lu, RPI, Peaks in Packaging, 2003

Through-Silicon Via (TSV)

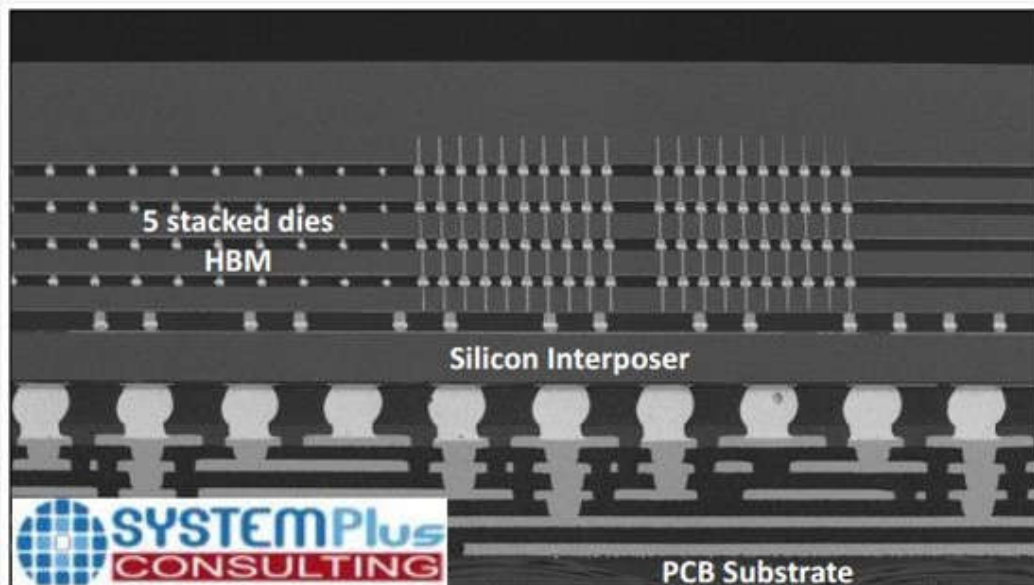
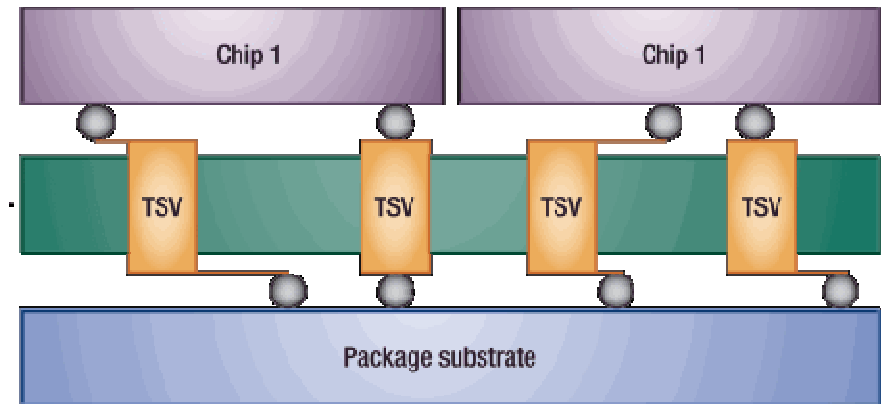
Conductive channels through the silicon wafer



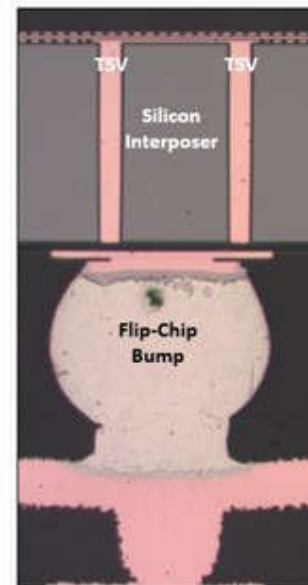
Silicon Interposer

A conductive interface between chips and substrates

interposer



SEM Cross-Section with HBM stacked on a Silicon interposer

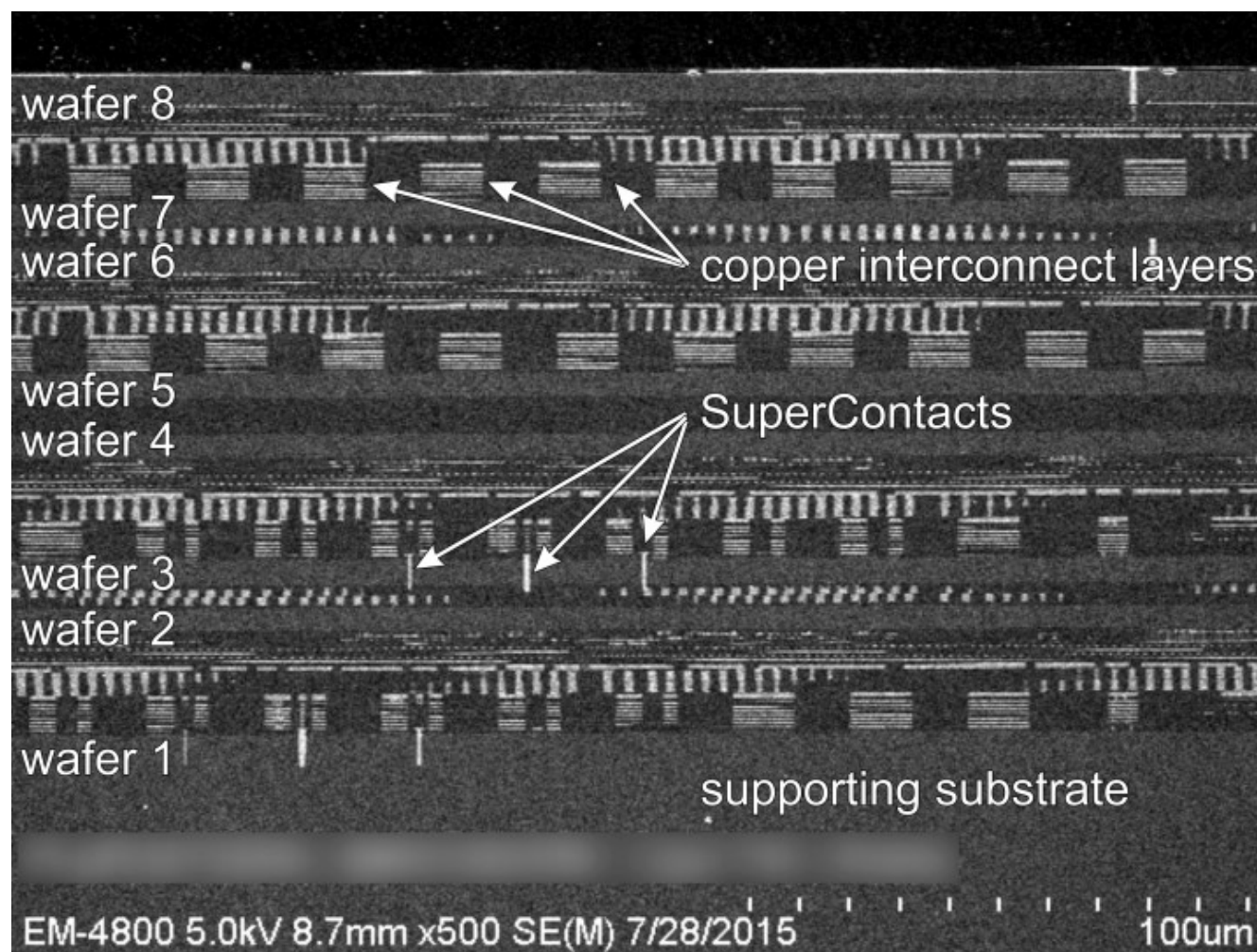


AMD interposer Cross-Section

Q: Why shall we use Si?

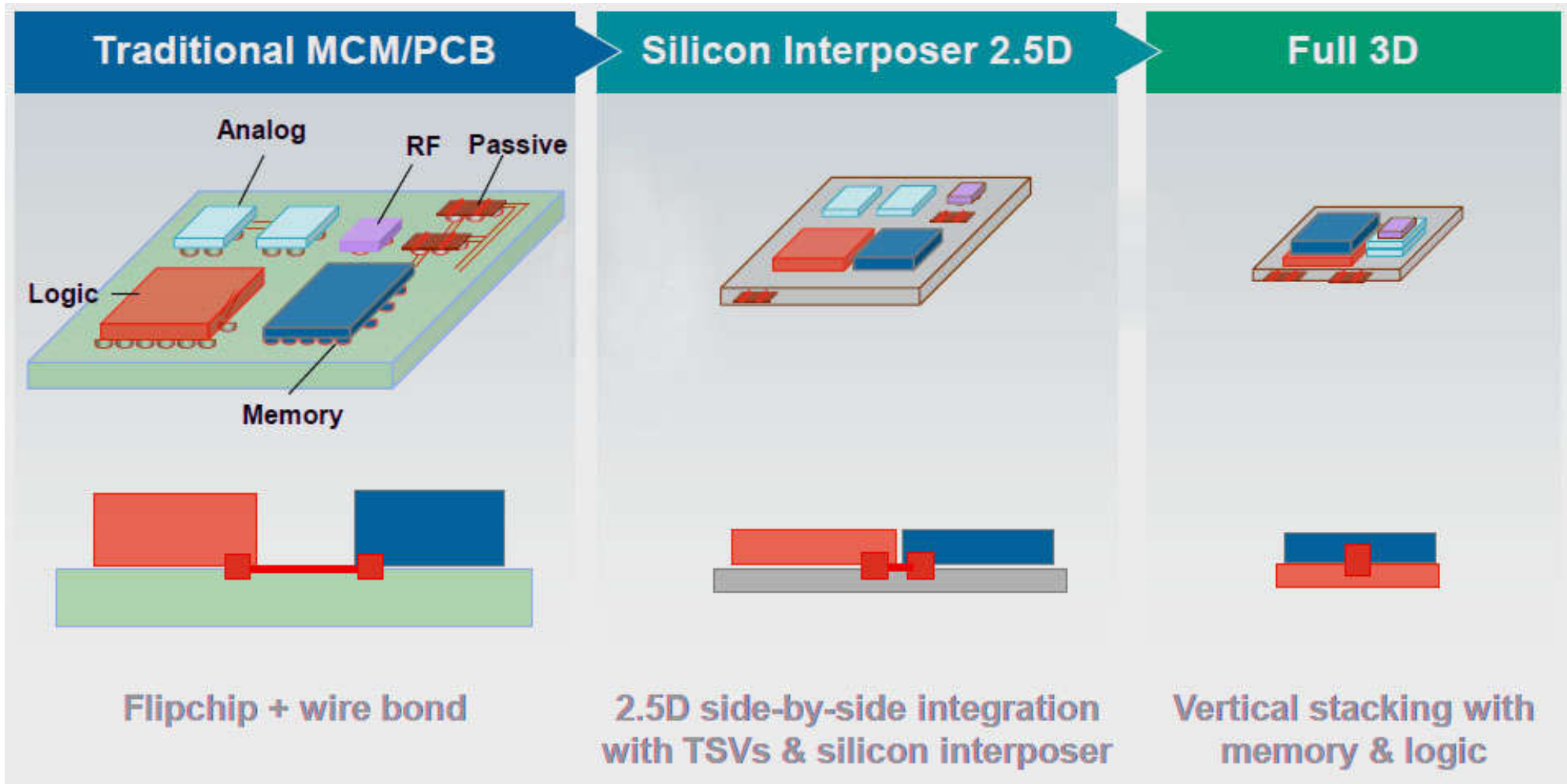
Memory Chips

- Increase the memory volume by 3D chip stacks



2D -> 2.5D - 3D

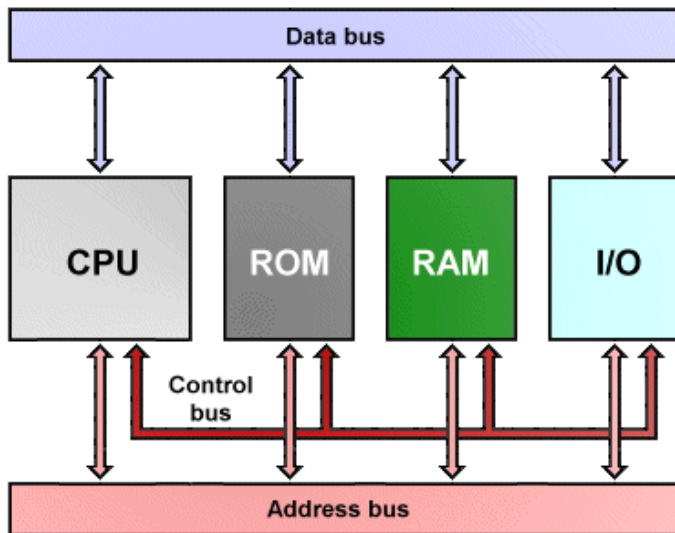
reduced size, faster speed, higher performance, ...



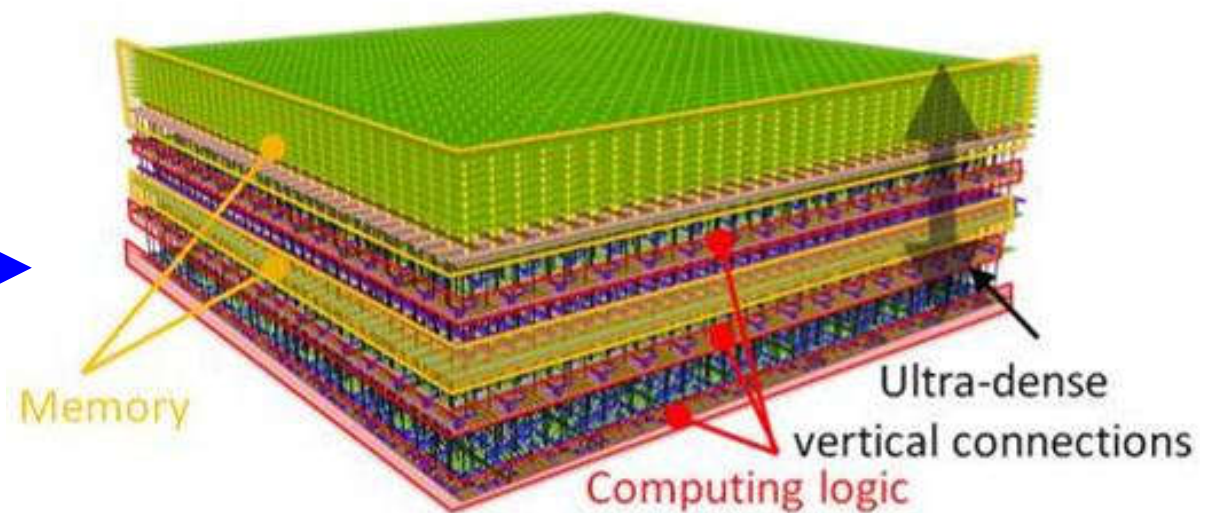
[Video](#)

3D IC

- Logic + Memory + Sensing + ...

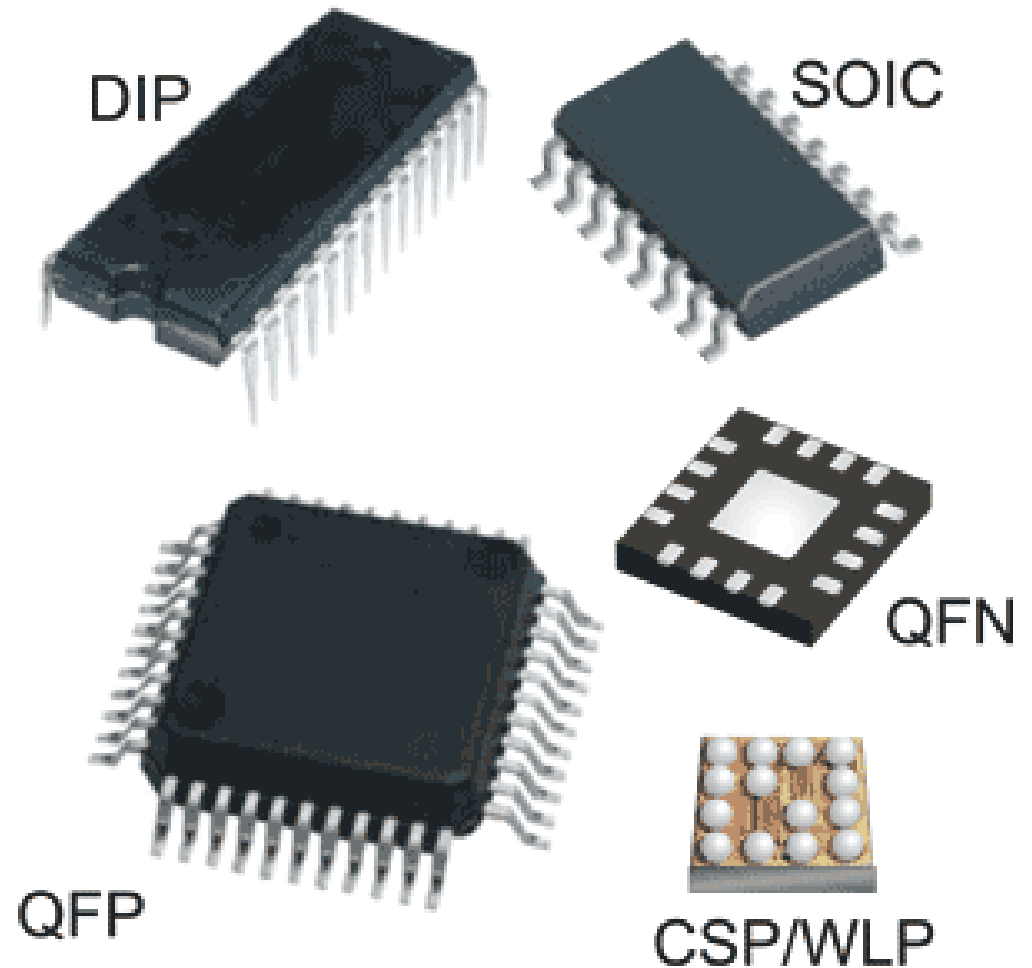
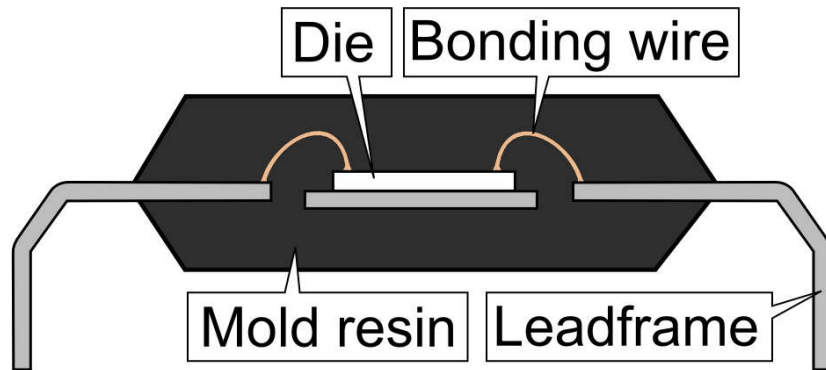


conventional



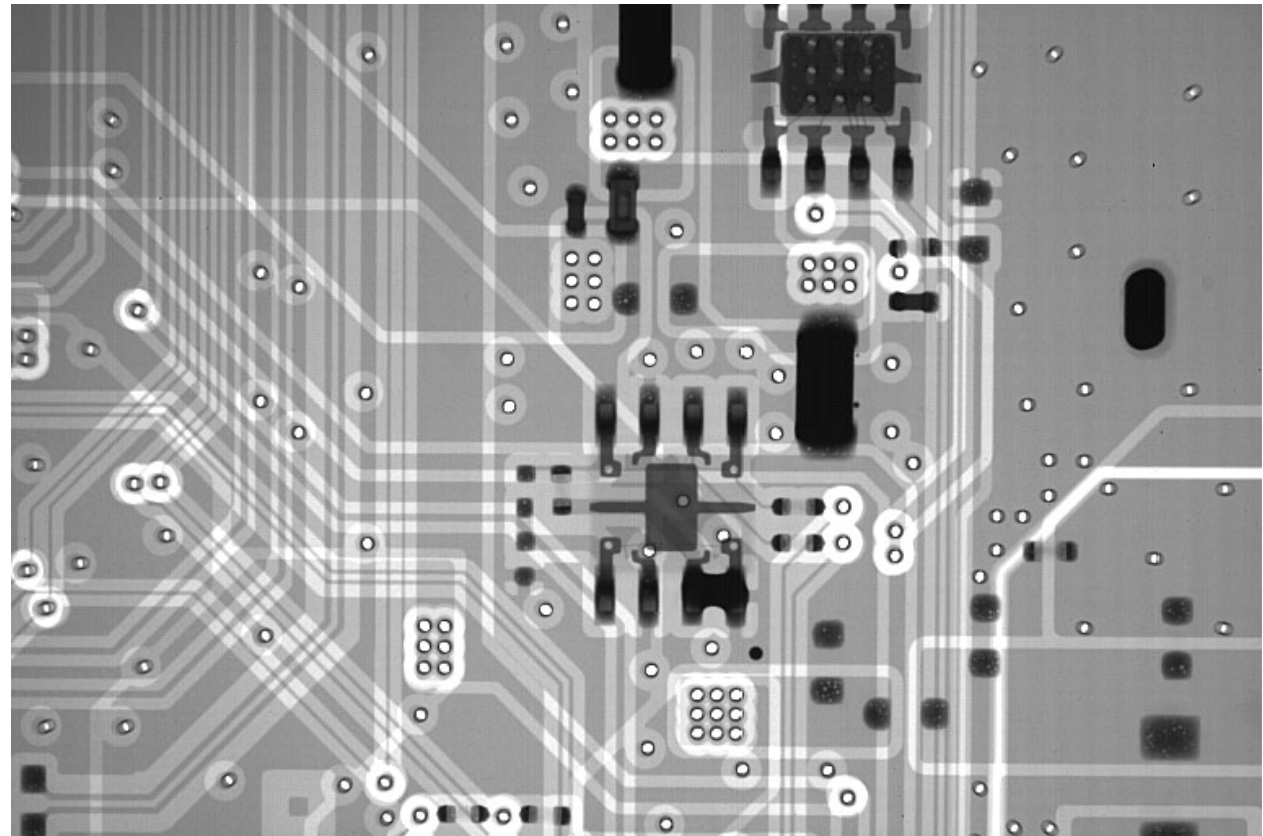
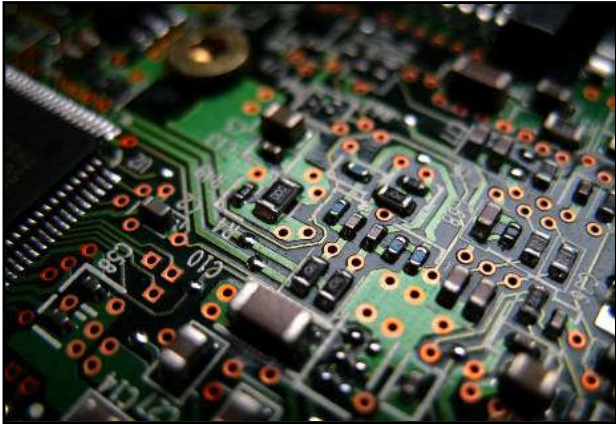
3D IC

Chip Packaging



Q: Why is the package black?

X-ray Inspection of Circuit

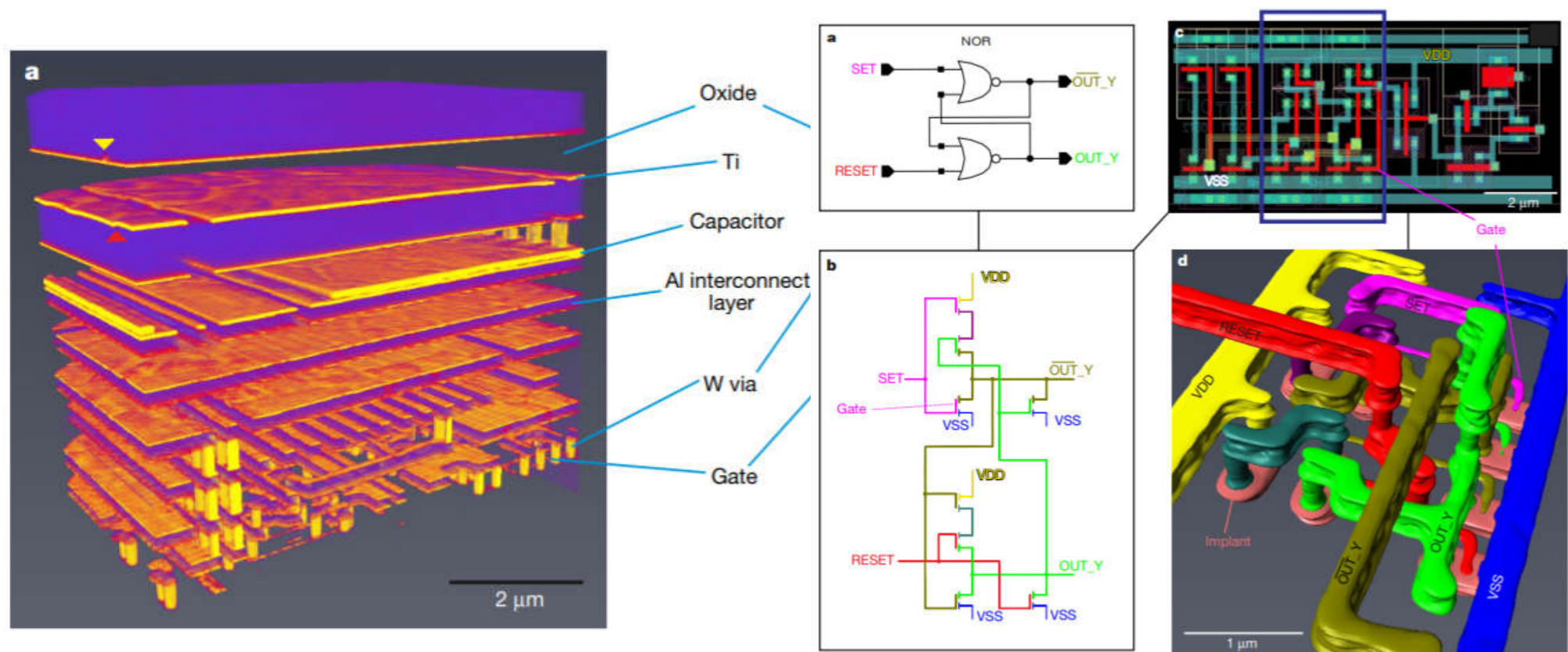


X-ray image

X-ray Inspection of Circuit

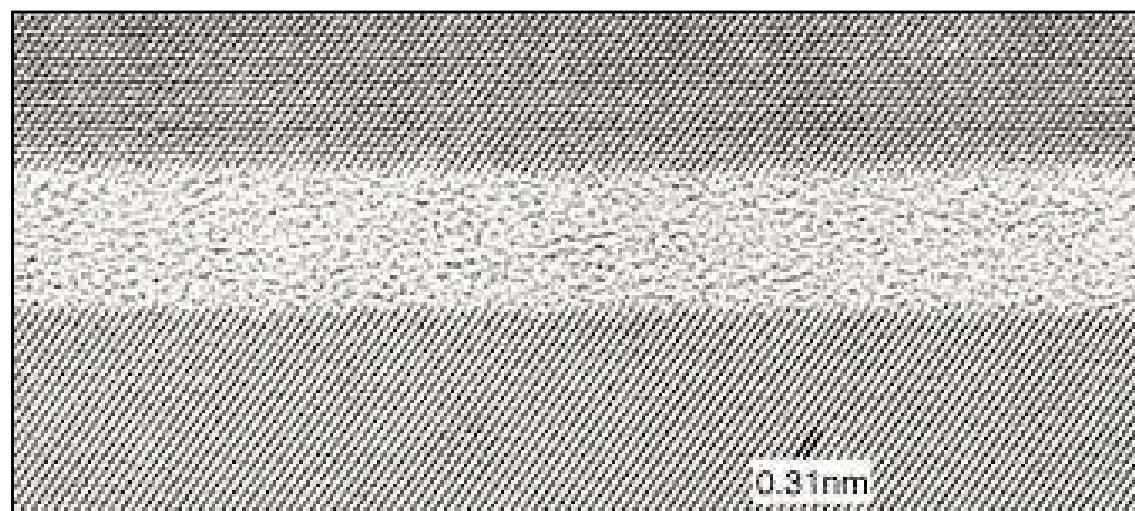
High-resolution non-destructive three-dimensional imaging of integrated circuits

Mirko Holler¹, Manuel Guizar-Sicairos¹, Esther H. R. Tsai¹, Roberto Dinapoli¹, Elisabeth Müller¹, Oliver Bunk¹, Jörg Raabe¹ & Gabriel Aeppli^{1,2,3}



Wafer Bonding

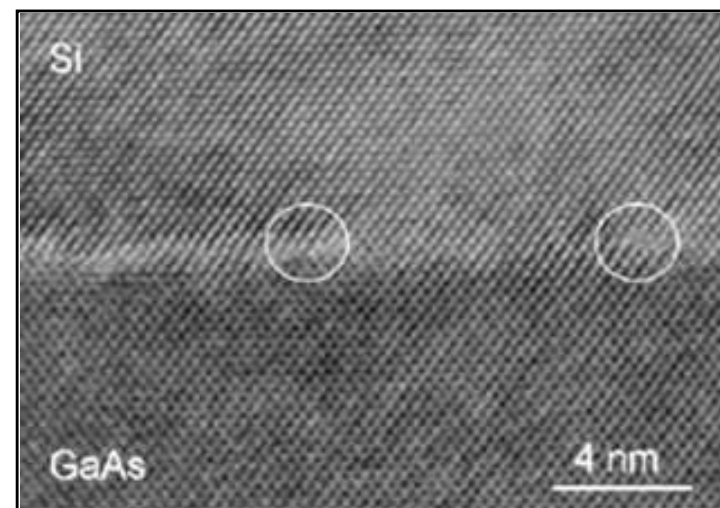
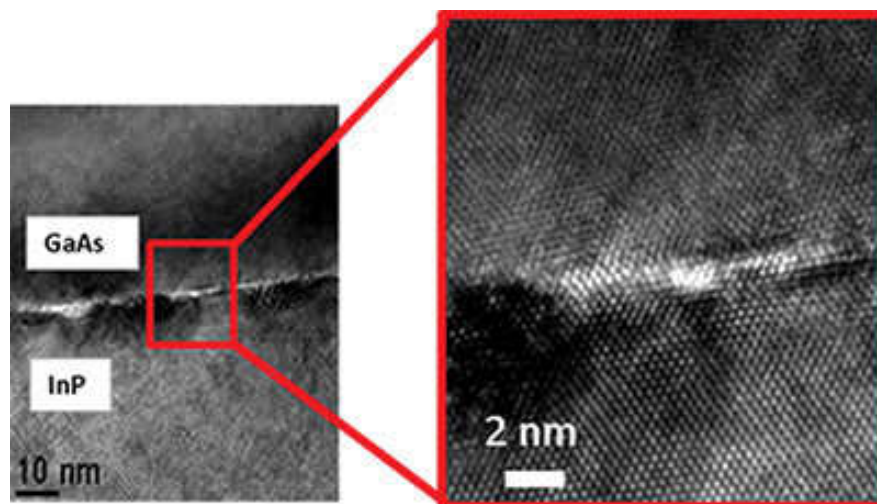
when direct growth is difficult ...



Si

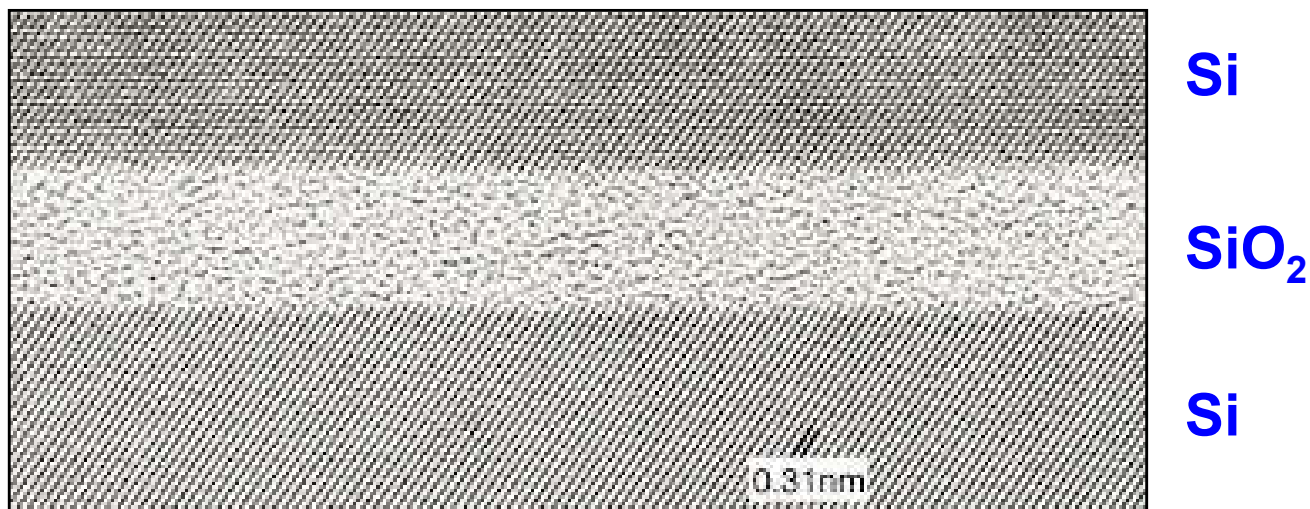
SiO₂

Si



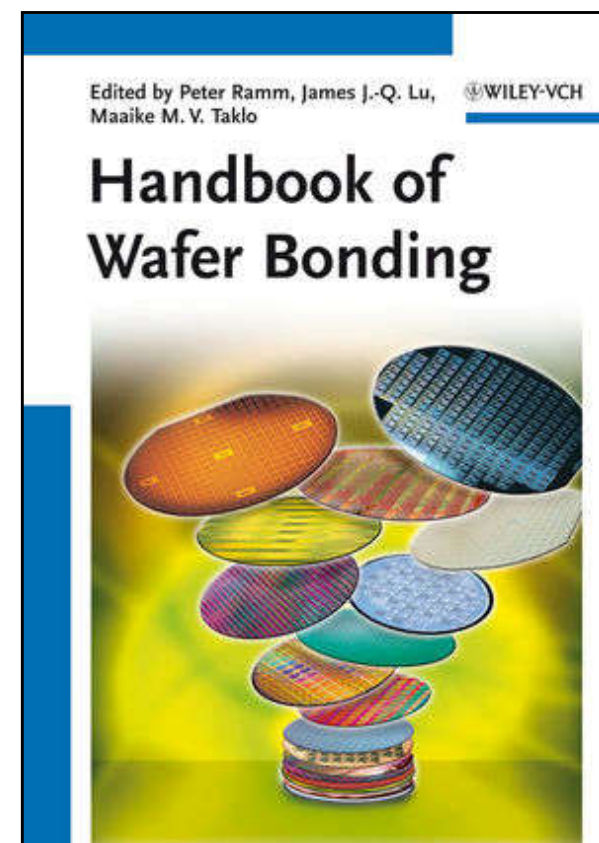
Wafer Bonding

- **Direct wafer-wafer bonding**
 - **very clean and smooth surface**
 - **high temperature (> 1000 °C) for atom diffusion**

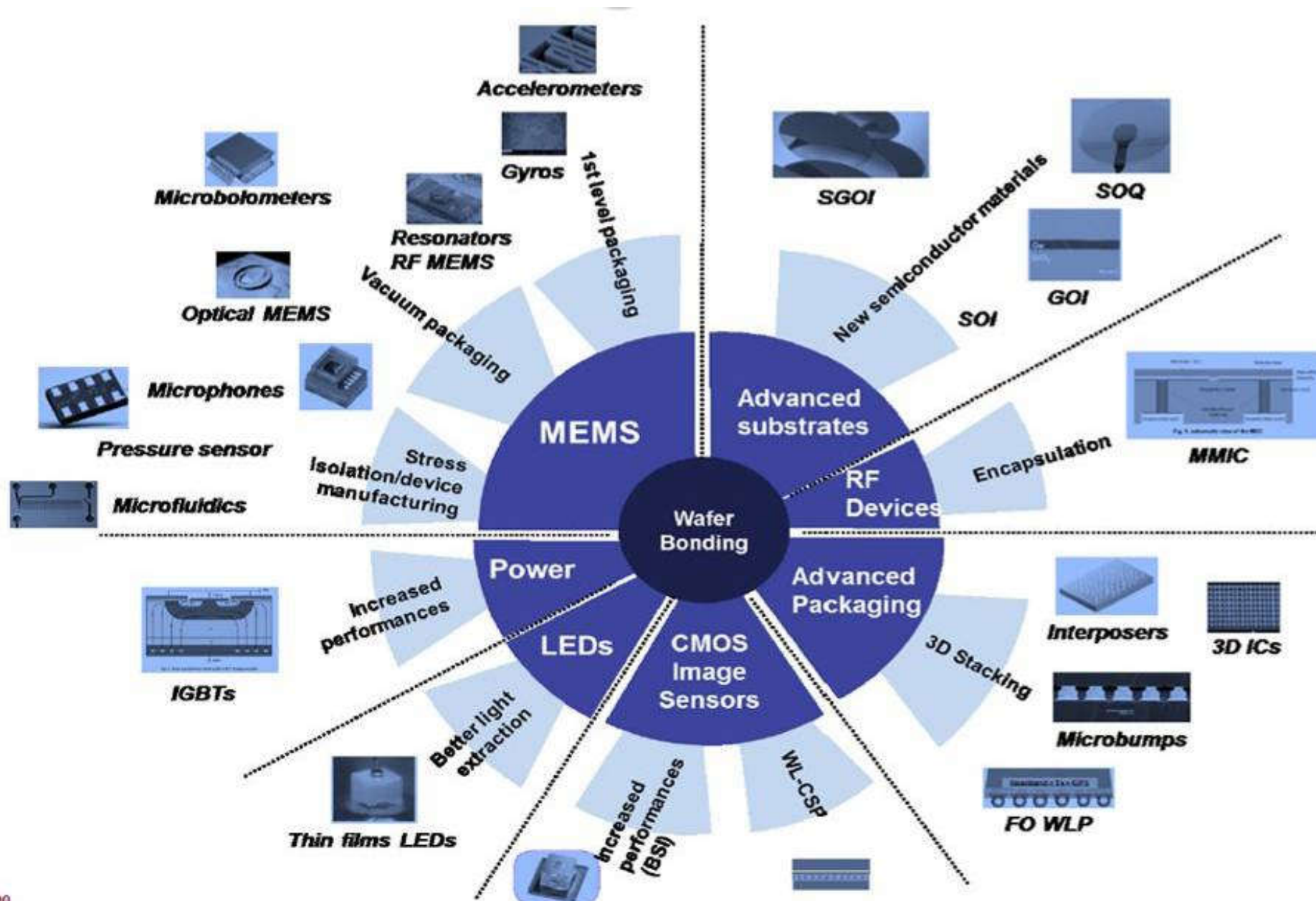


Wafer Bonding

- Direct bonding
- Surface activated bonding
- Plasma activated bonding
- Anodic bonding
- Eutectic bonding
- Glass frit bonding
- Adhesive bonding
- Thermocompression bonding
- Reactive bonding
- Transient liquid phase diffusion bonding
- ...

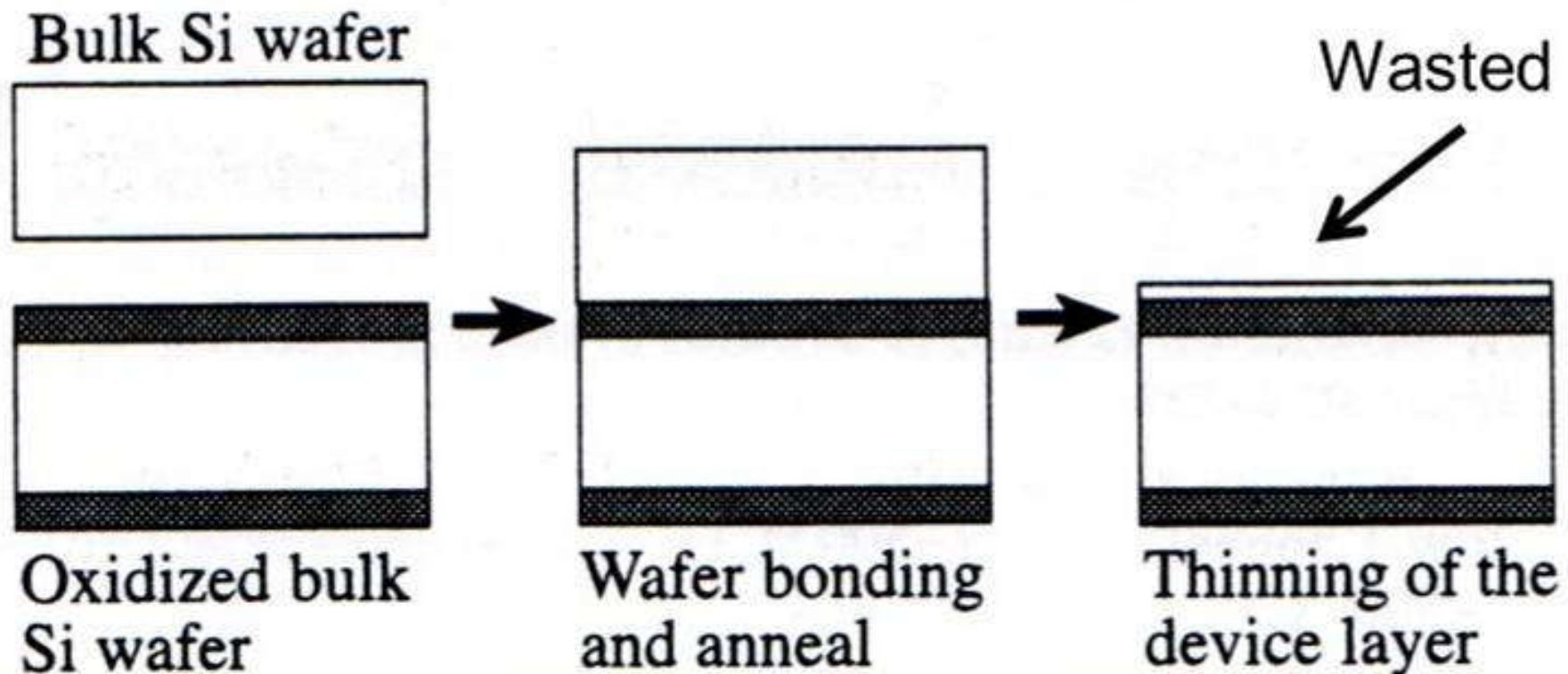


Wafer Bonding: Applications



Make Silicon-on-Insulator (SOI)

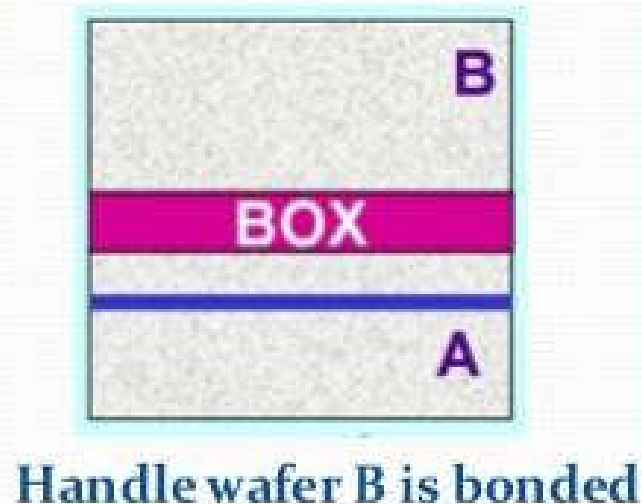
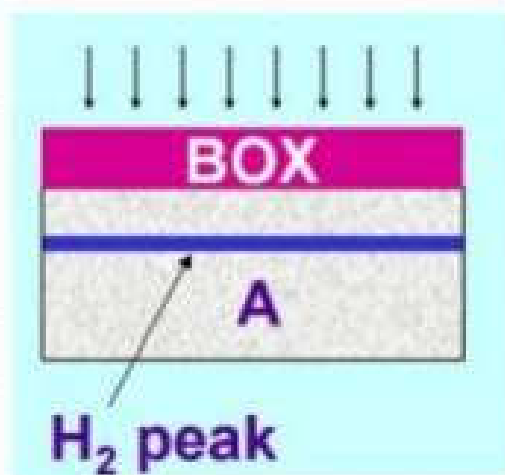
Bonding + Etch back



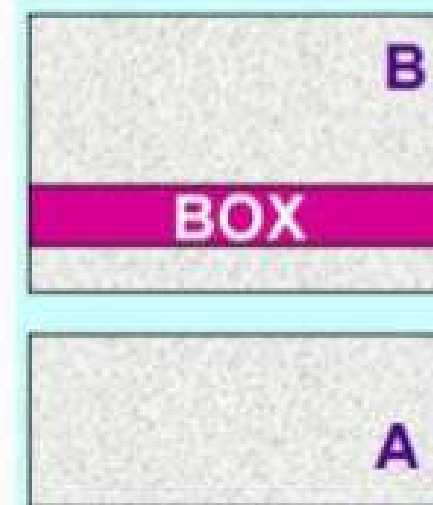
Make Silicon-on-Insulator (SOI)

'Smart-Cut'

Hydrogen implantation
through thermal oxide
dose $\sim 1-5 \times 10^{16} \text{ cm}^{-2}$



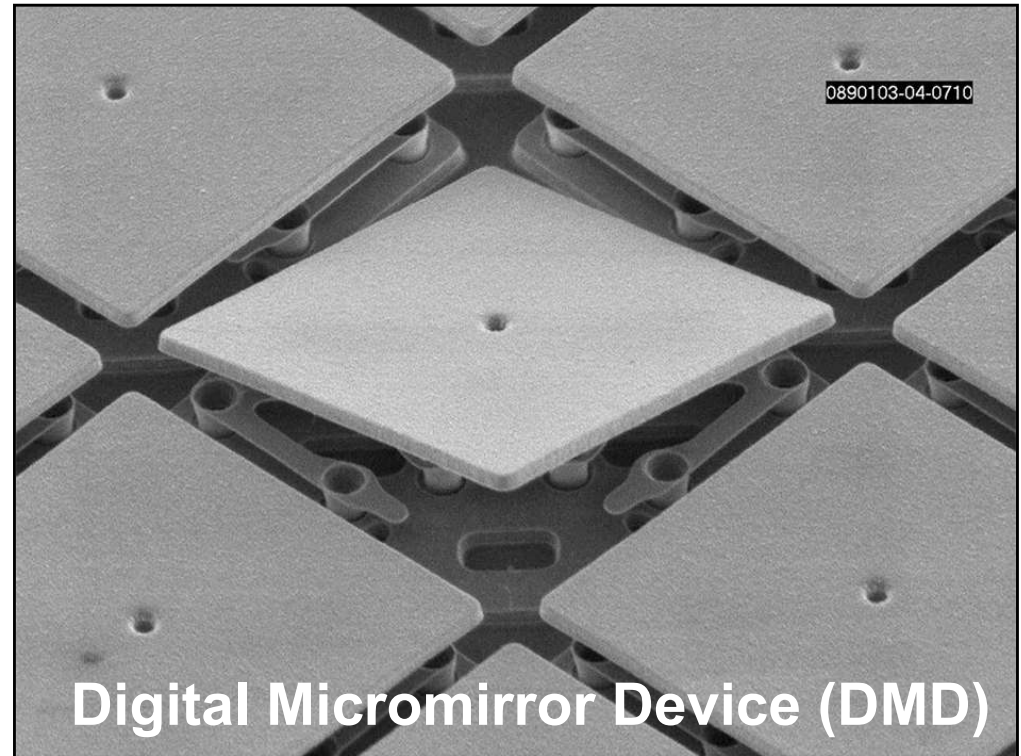
At $\sim 400-600^\circ\text{C}$ wafer
A separates from B
at H₂ peak



After low temperature splitting, SOI wafer (B) is annealed $\sim 1100^\circ\text{C}$ to strengthen the bond, whereas wafer A is reused. SOI film thickness set by H₂ implant energy and BOX thickness

MEMS

- **Micro-Electro-Mechanical Systems (MEMS)**

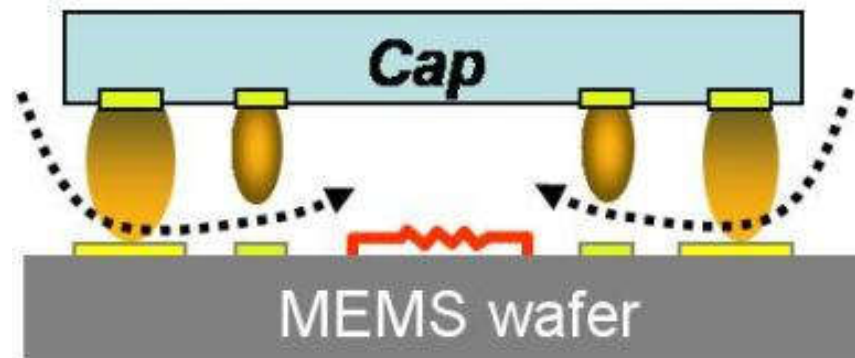


Digital Micromirror Device (DMD)

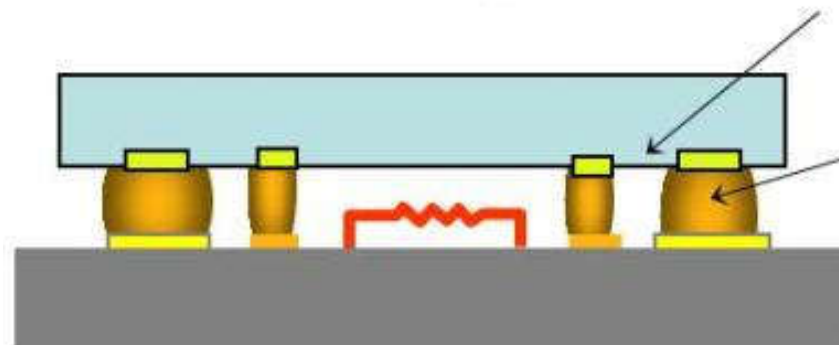
[Video](#)

MEMS

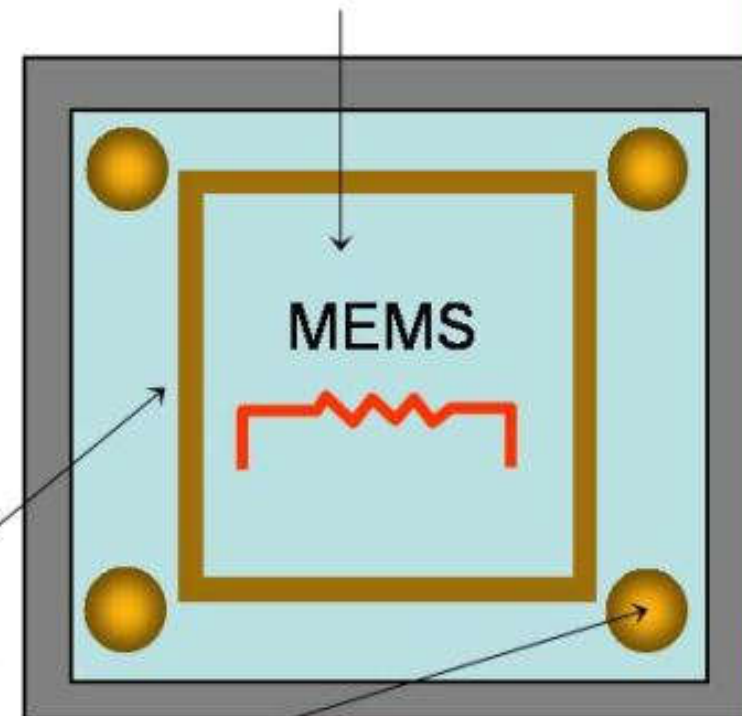
1. Oxide reduction
2. Vacuum
3. Gettering



4. Controlled Collapse
Hermetic Sealing

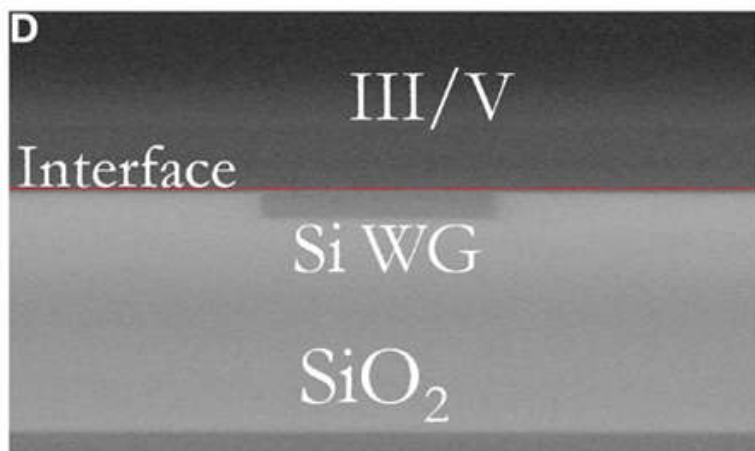
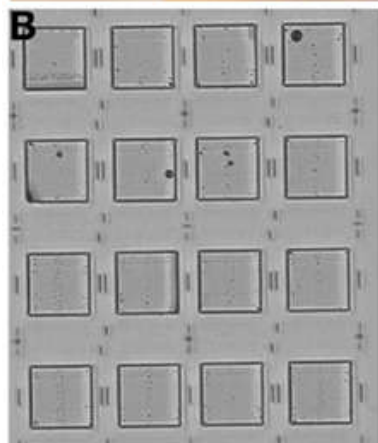
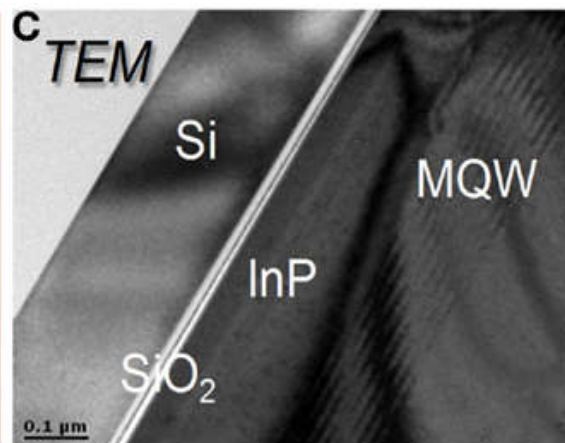
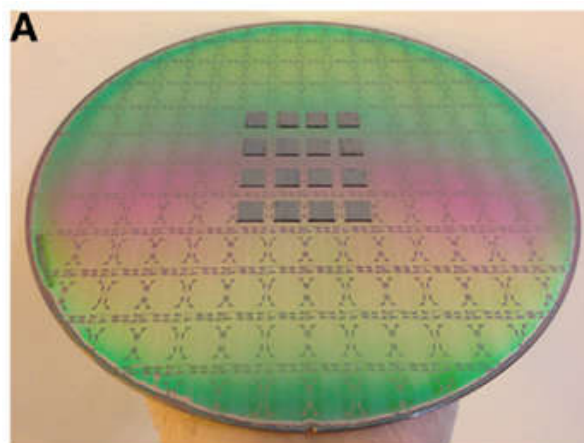
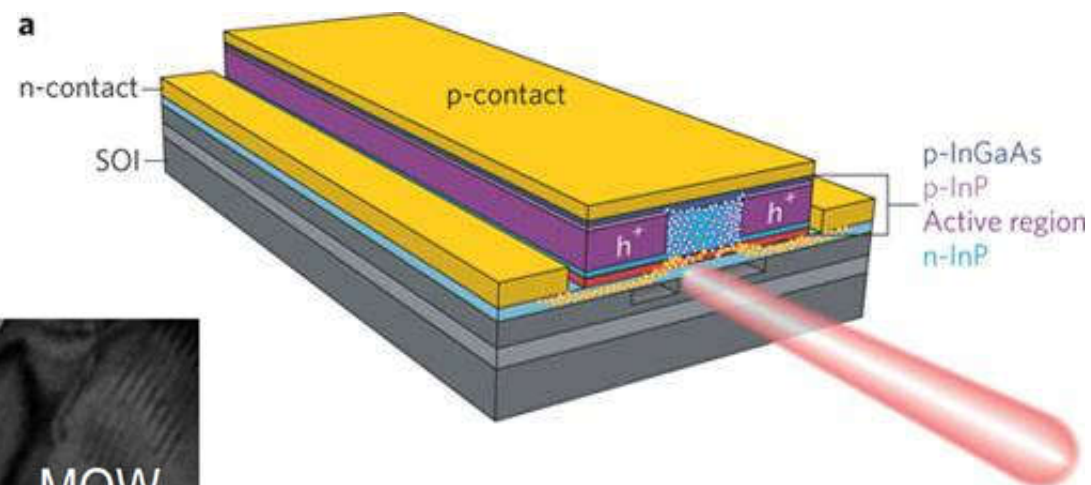


Controlled atmosphere
or vacuum

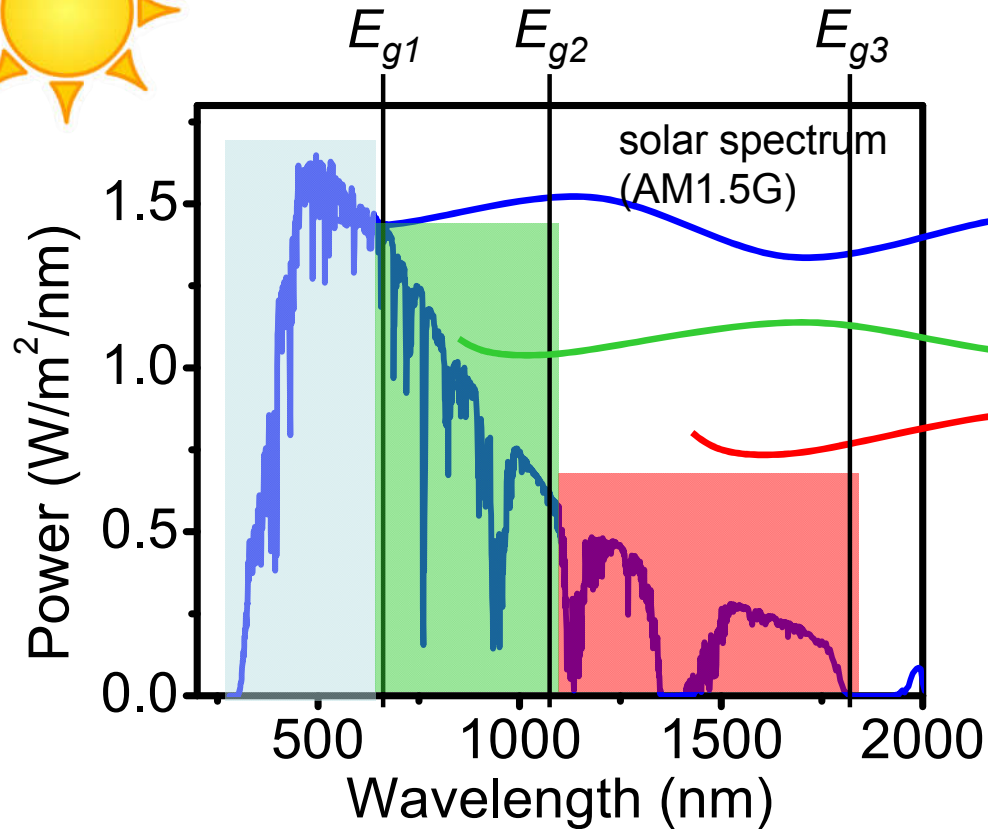
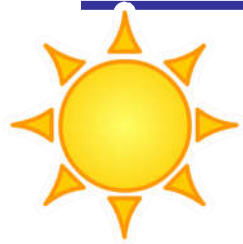


interconnection

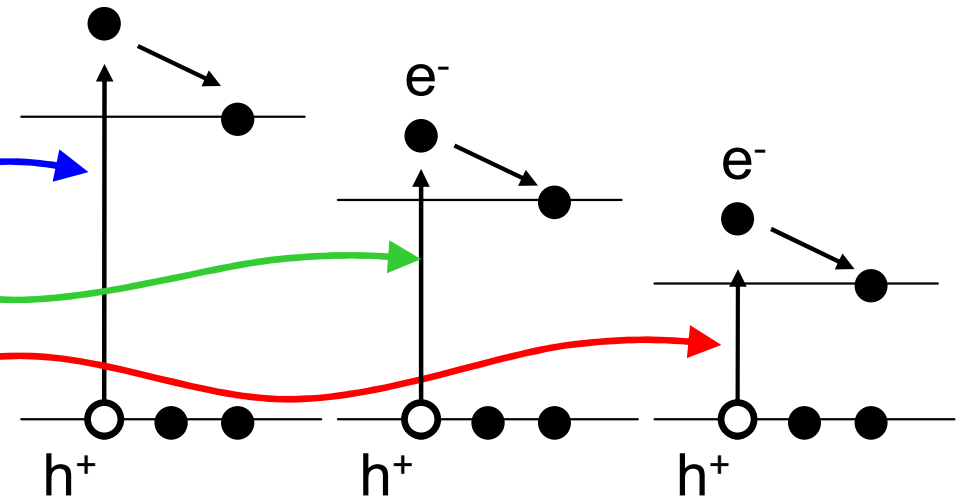
III-V Lasers on Si



Multijunction (MJ) Solar Cells



ASTM G173-03

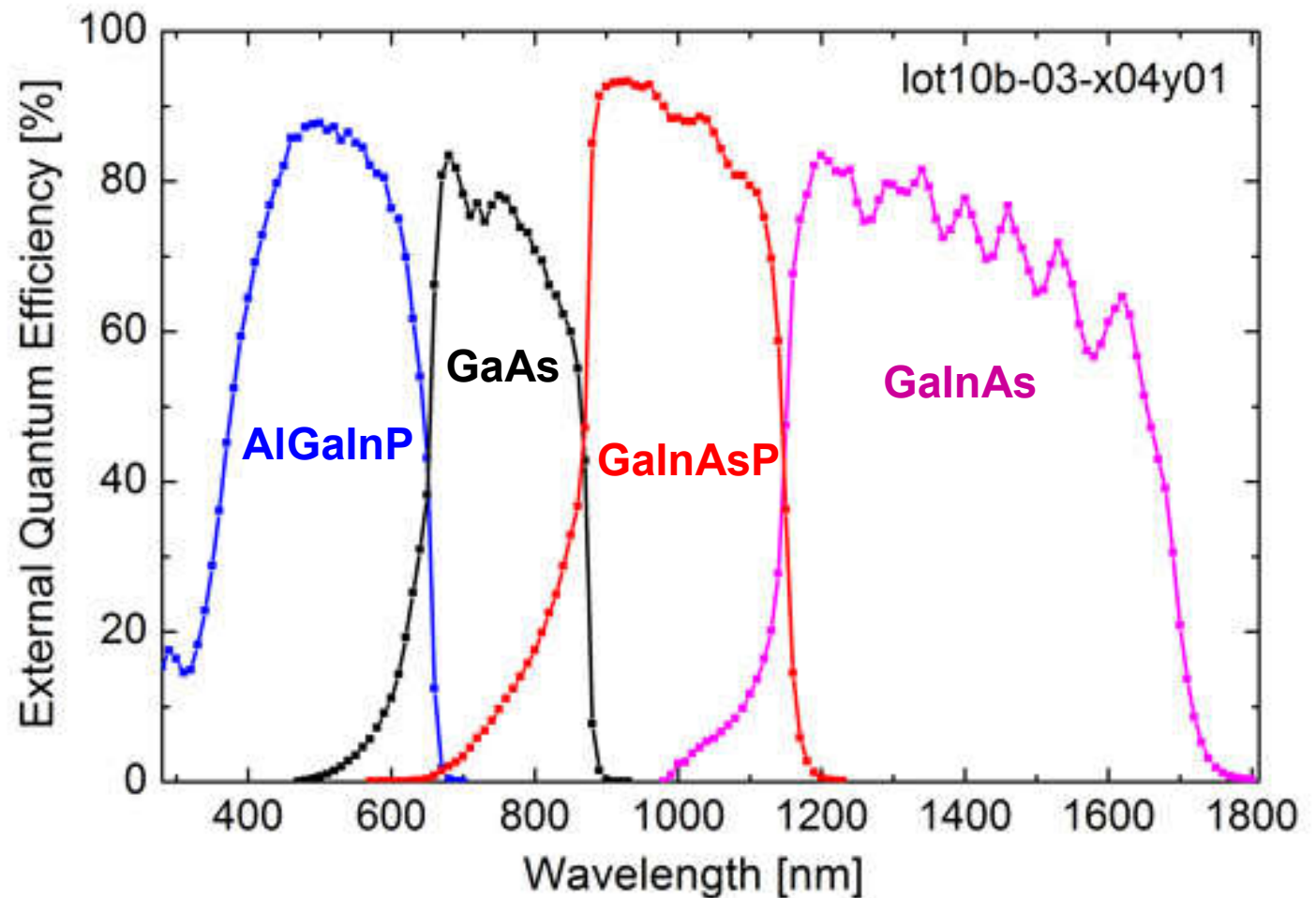
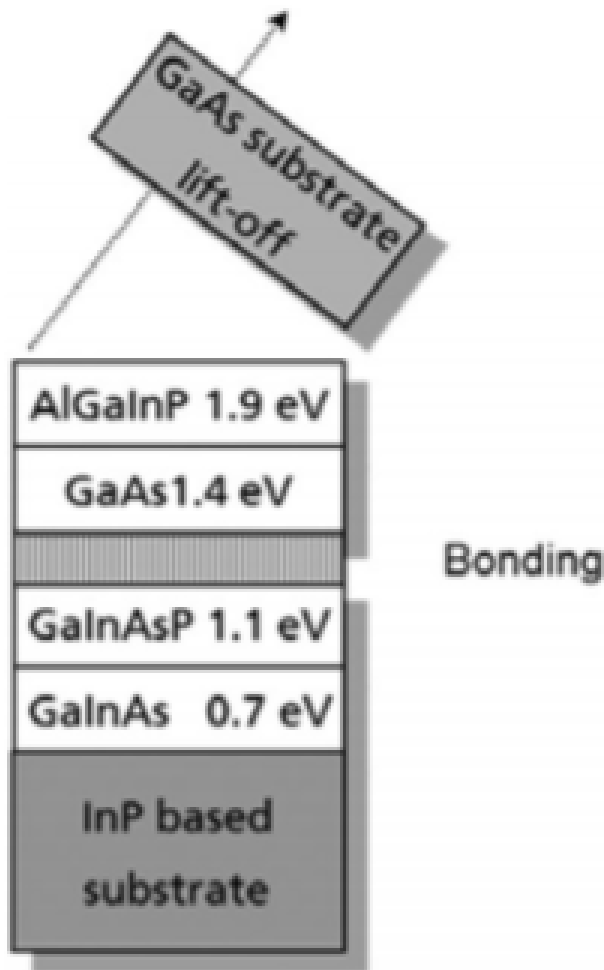
1J: $\eta = 37\%$ 2J: $\eta = 50\%$ 3J: $\eta = 56\%$ infinite J: $\eta = 72\%$

Use the entire solar spectrum

W. Shockley and H. A. Queisser, *J. Appl. Phys.* **32**, 510 (1961)C. H. Henry, *J. Appl. Phys.* **51**, 4494 (1980)

Stacked MJ Solar Cells

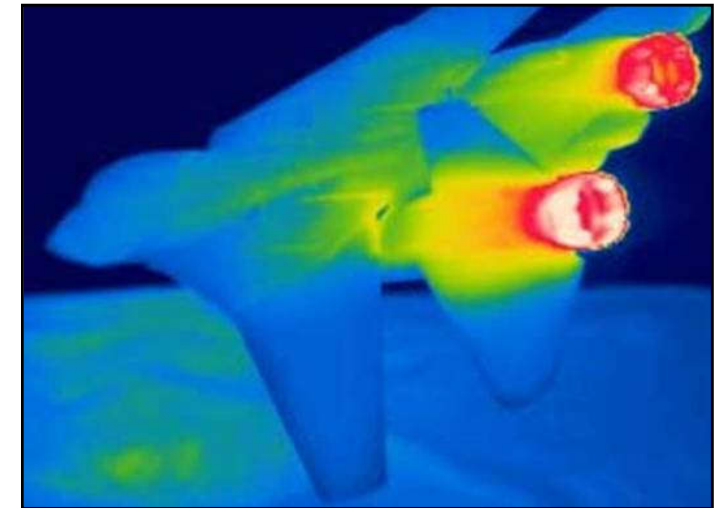
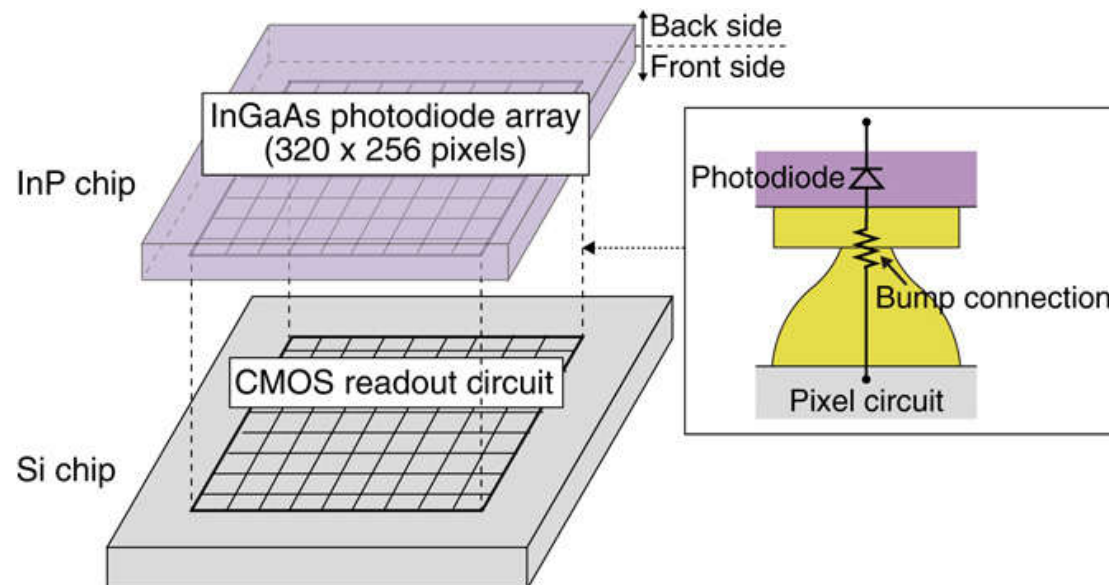
bonded AlGaInP/GaAs // GaInAsP/GaInAs solar cells



World record efficiency: 46%

UV and IR Imaging Sensors

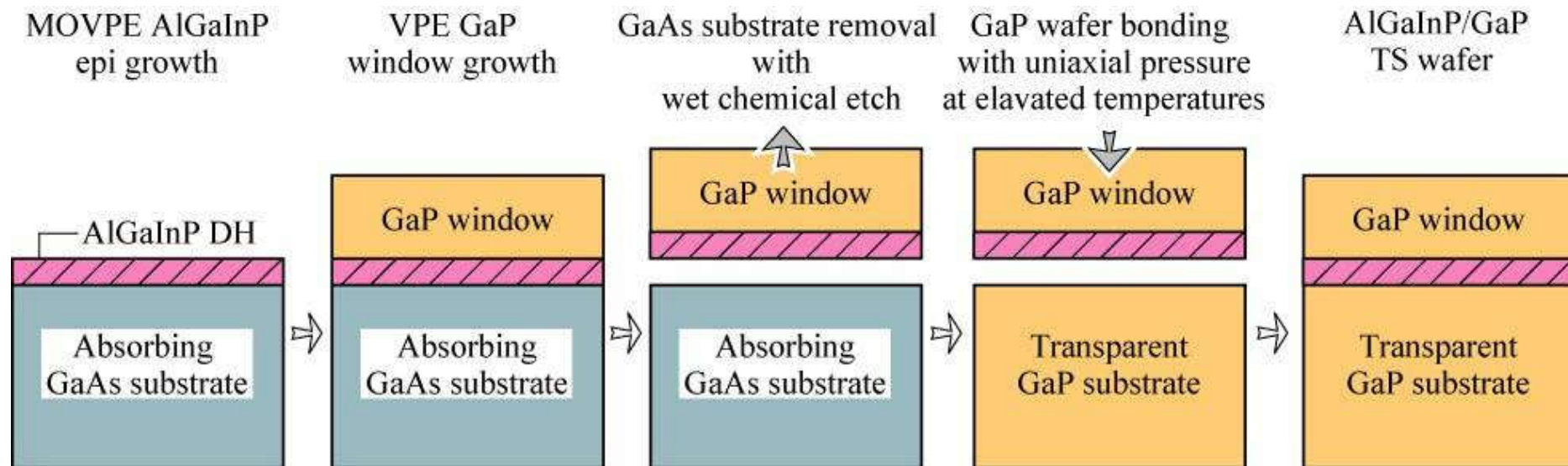
- Silicon only absorbs well from 400 nm to 1100 nm
- IR sensors: InGaAs, HgCdTe, ...
- UV sensors: GaN, ...
- sensor arrays bonded with Si circuits



infrared imaging

Red LEDs

- AlGaInP red LEDs grown on GaAs substrates
- GaAs strongly absorbs red light
- GaP is transparent in red, but not lattice matched
- bond LEDs on GaP, and remove GaAs



Blue LEDs

- GaN blue LEDs grown on sapphire substrates
- Sapphire is electrically and thermally insulating
- bonded onto a thermally conductive substrate

